



Estimation of the depletion capacitance in a monolithic pixel sensor

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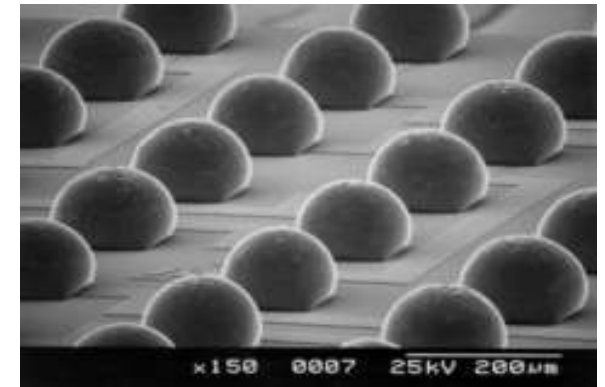
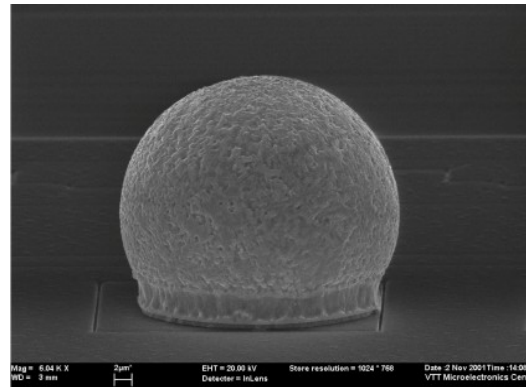
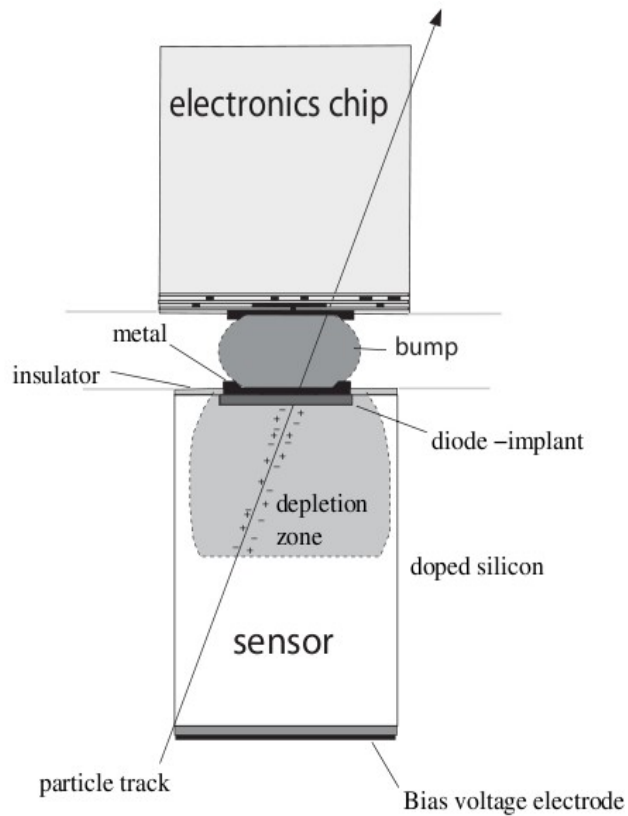
Turin, 15/05/2013

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Outline

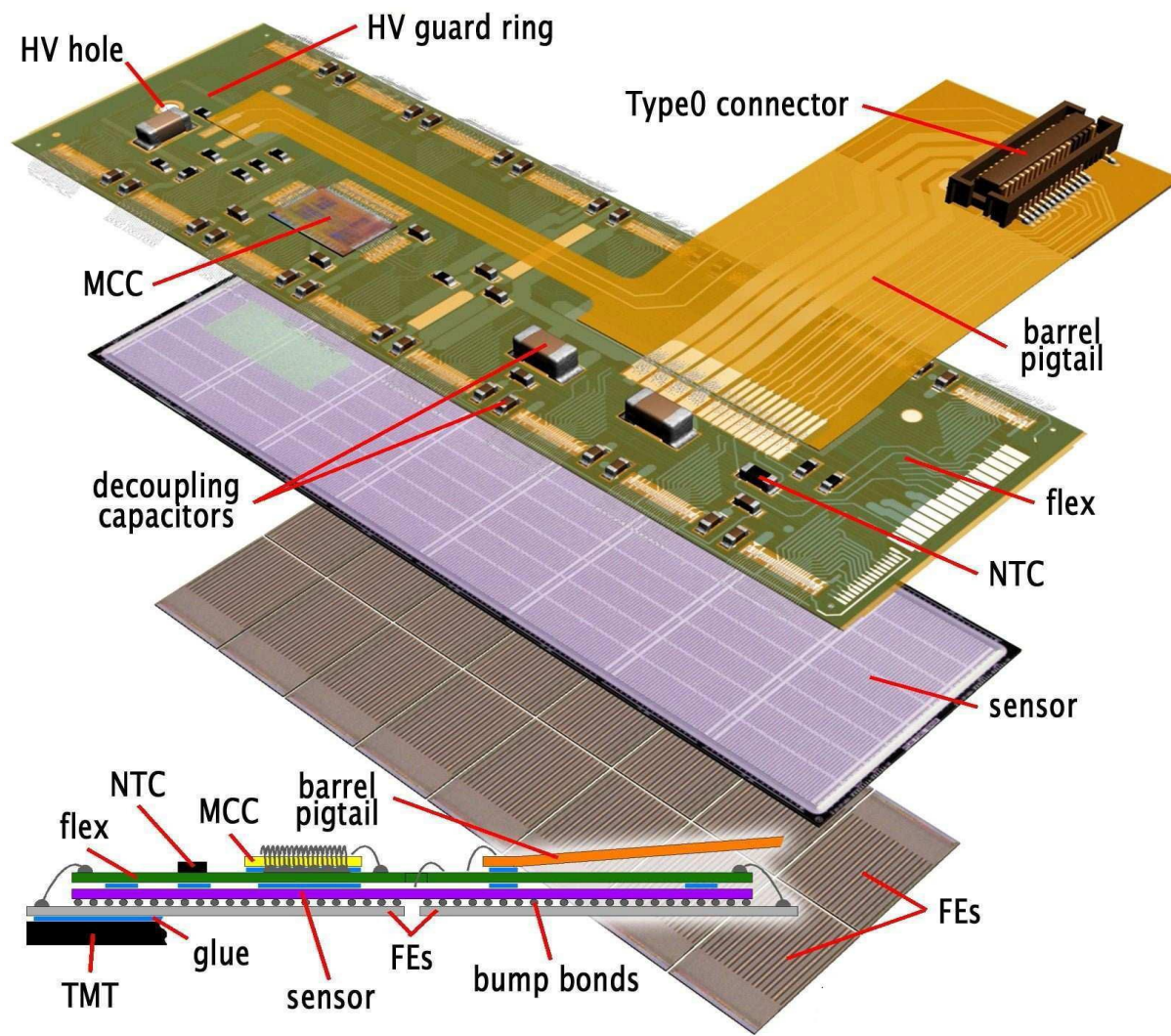
- *monolithic pixel sensors*
- *pixel matrix segmentation*
- *on-chip and off-chip read-out electronics*
- *DAQ system*
- *lab measurements*
 - *setup linearity*
 - *sensor capacitance estimation*

Hybrid pixel detectors



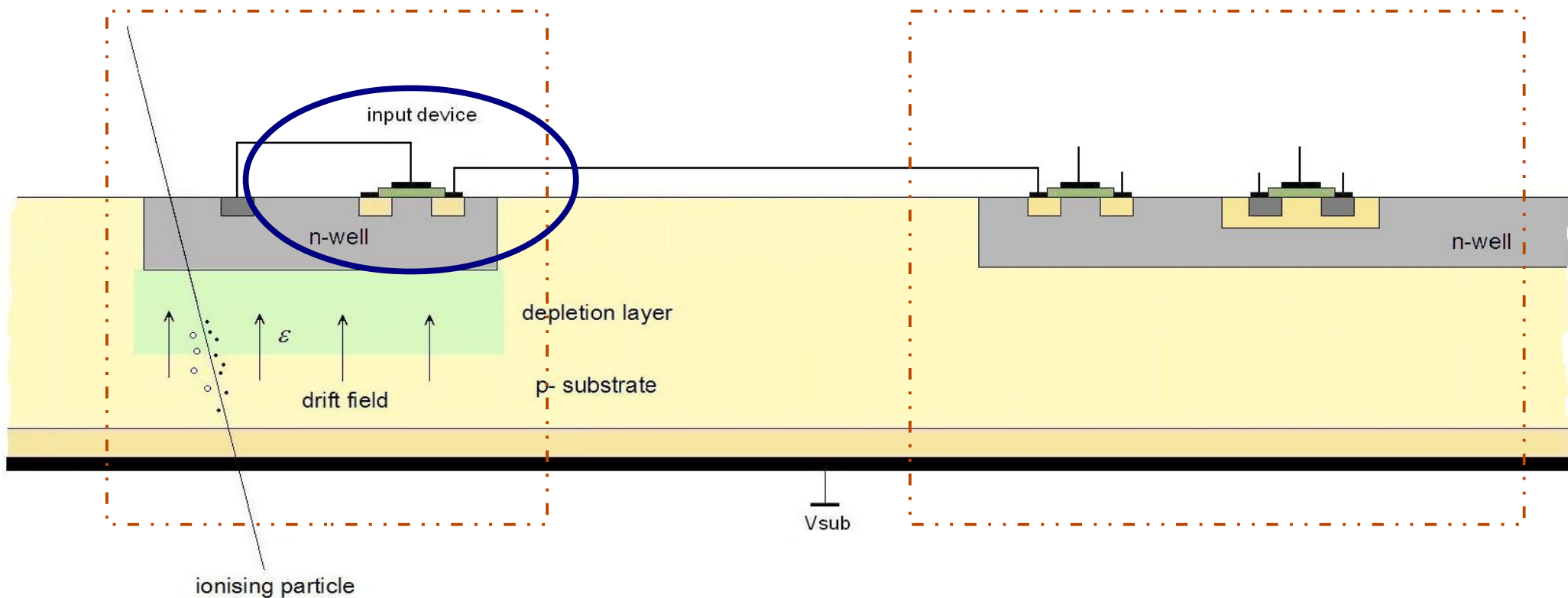
- sensor and electronics made on **two different silicon dies** and then mated together
 - **bump bonding** technique → expensive (cost can be afforded to cover max. area $\sim m^2$)
 - charge collection **by drift** → OK speed and radiation hardness
 - power consumption $\sim 250 \text{ mW/cm}^2$
 - material budget $\sim 300 \mu\text{m}$

Full module example (ATLAS)



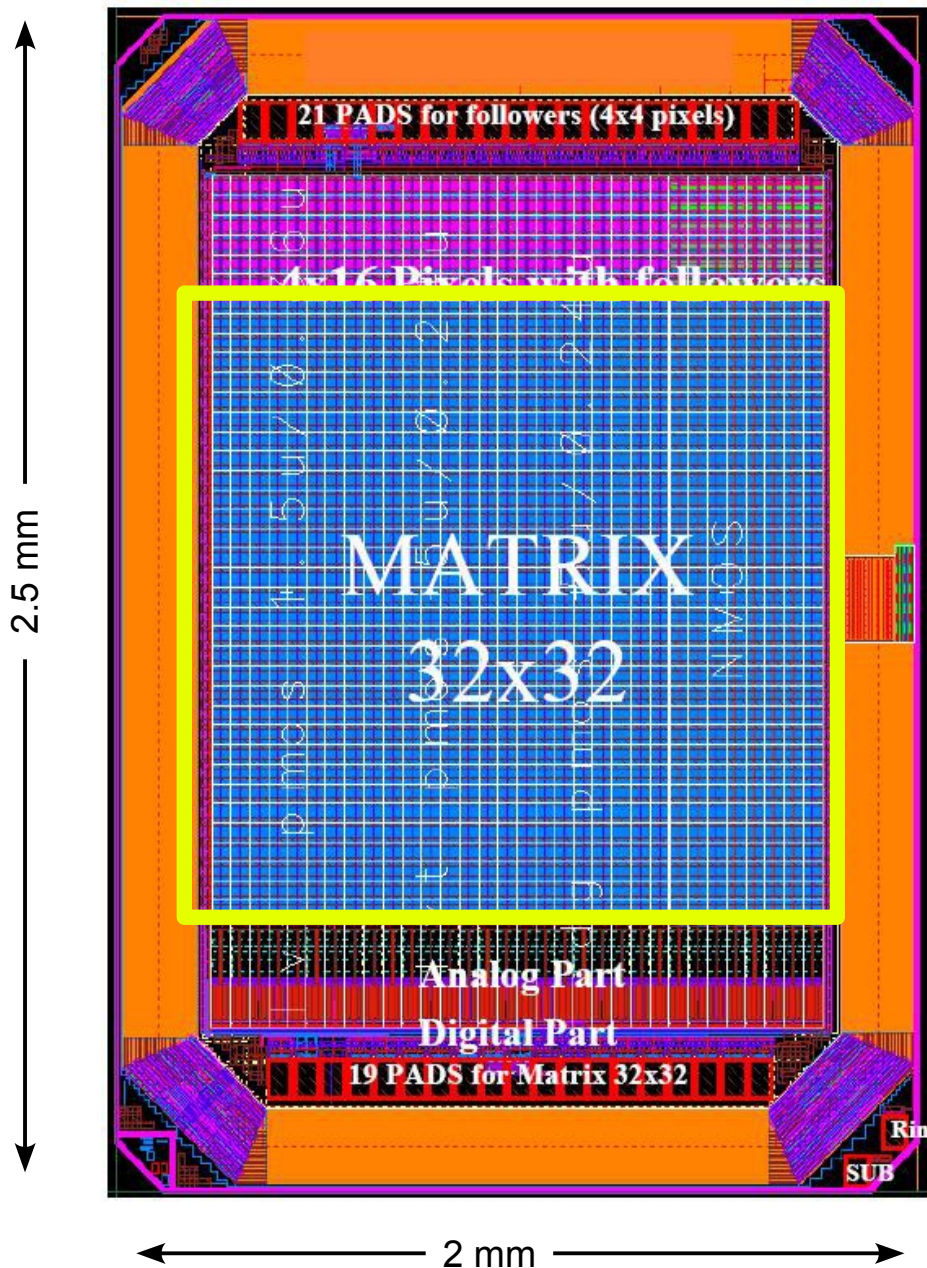
on-pixel

in the chip periphery



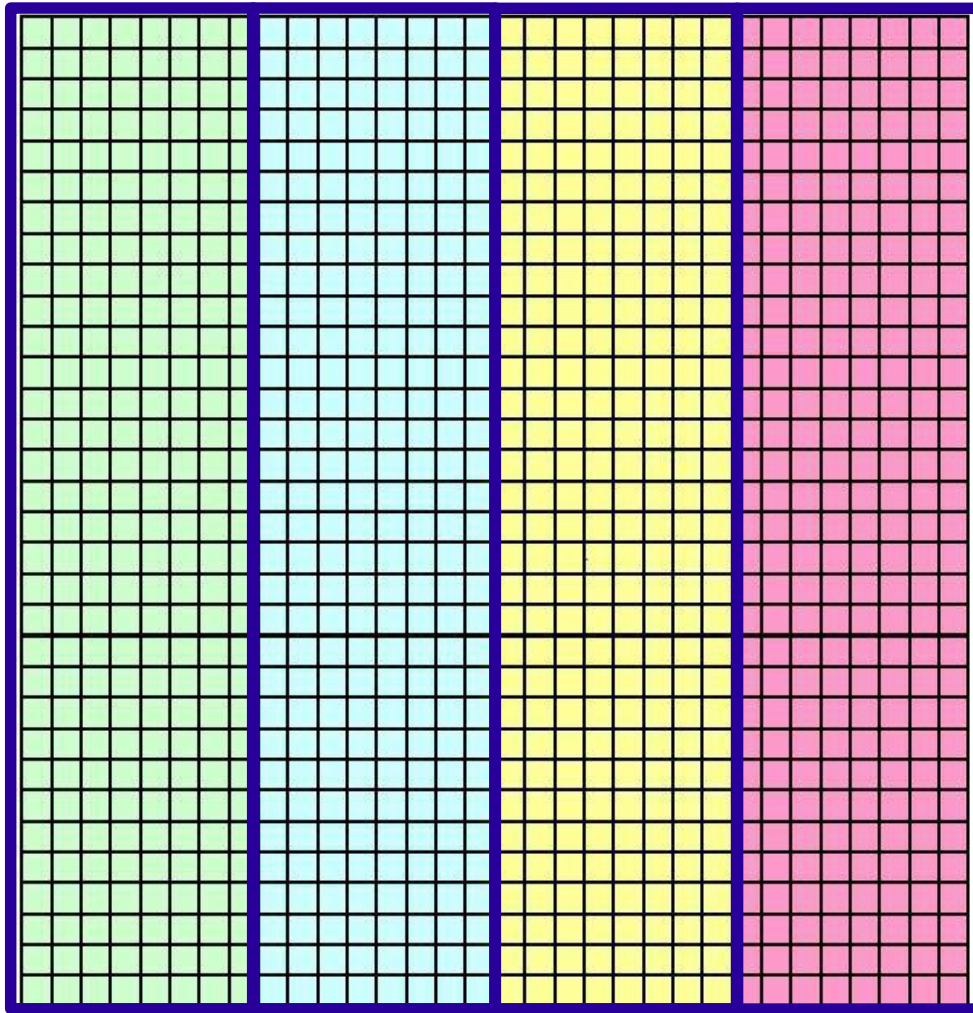
- 90 nm **commercial** CMOS technology
- **reverse biased substrate** ($\sim -30V$) \rightarrow charge collection **by drift**
- the **first transistor** of the analog front-end electronics is built at the top of each the pixel !
- the remaining electronics is placed in a dedicated n-well **at the periphery** of the sensitive region
 - the n-well must be **insulated** from the reverse biased substrate to avoid **breakdown** !

Matrix segmentation (1)



- sensitive area + read-out electronics are integrated on the same chip !
 - monolithic approach
 - no separation between sensor and electronics
- a guard ring structure (200 μm around the matrix) ensures a uniform depletion region
- two asymmetric regions in the matrix
 - TOP part \rightarrow 6 rows x 32 columns
 - CORE part \rightarrow 32 rows x 32 columns
- only CORE part pixels (1024 pixels) will be used for lab measurements

Matrix segmentation (2)



thin oxide
PMOS (1)

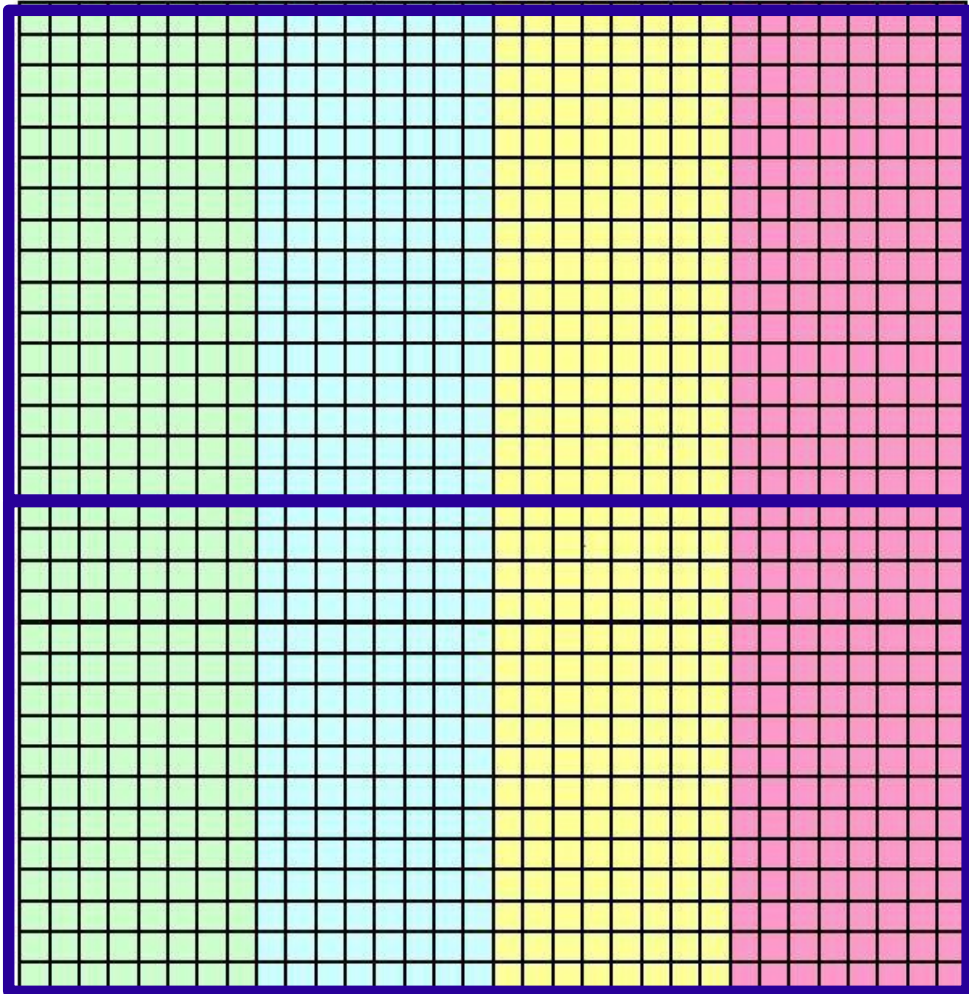
thin oxide
PMOS (2)

thick oxide
PMOS

thin oxide
NMOS

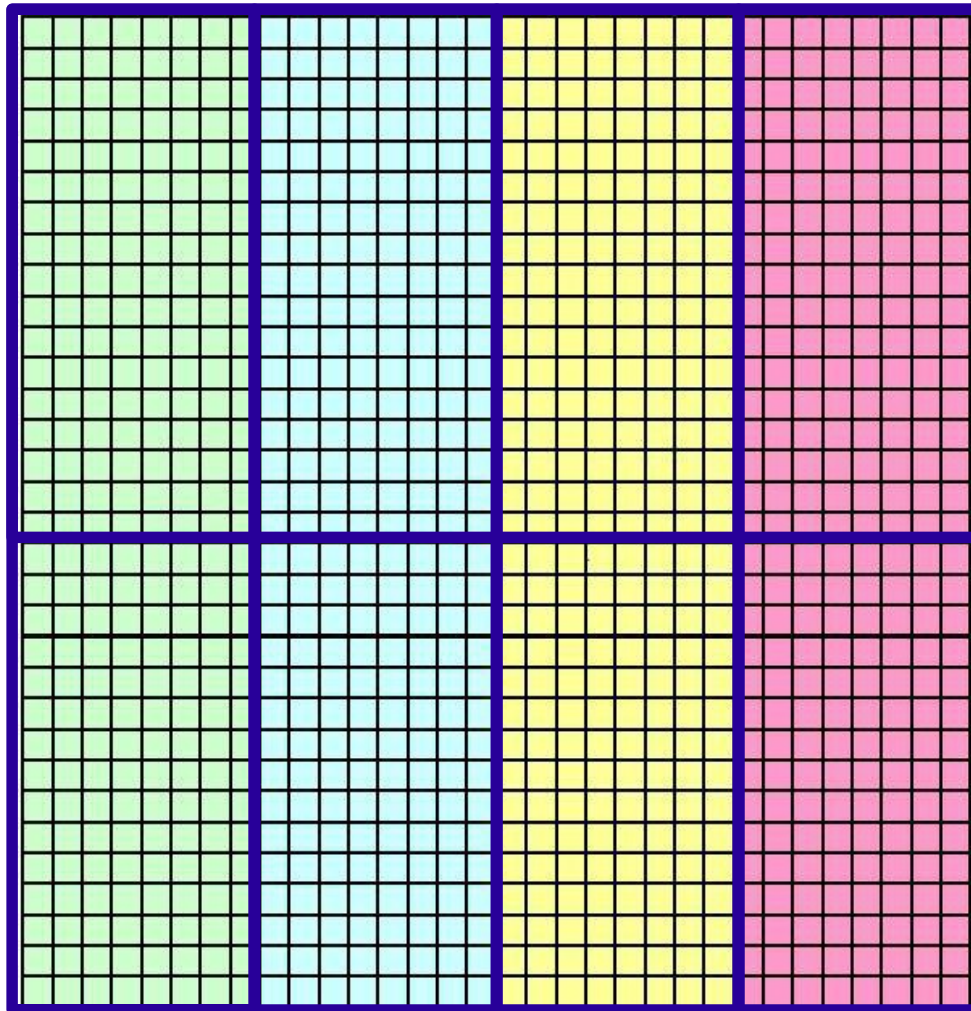
- different options have been implemented for the on-pixel transistor
- vertical segmentation → pixels with ***4 different types of input transistor***
 - 8 columns thin oxide PMOS (1)
 - 8 columns thin oxide PMOS (2)
 - 8 columns thick oxide PMOS
 - 8 columns thin oxide NMOS
- due to the limited available area PMOS input devices are preferable

Matrix segmentation (3)



- each pixel cell needs to *discharge* the depletion capacitance after a particle hit has been detected
 - on-pixel *reset scheme* (next slide)
- horizontal segmentation → pixels with *2 different types of reset schemes*
 - 16 rows with *active reset*
 - 16 rows with *continuous reset*

Matrix overall layout



thin oxide
PMOS (1)

thin oxide
PMOS (2)

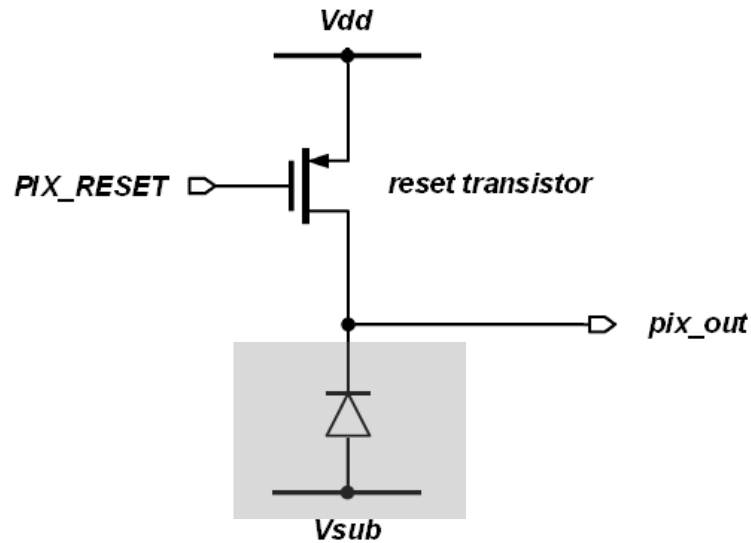
thick oxide
PMOS

thin oxide
NMOS

active reset

continuous reset

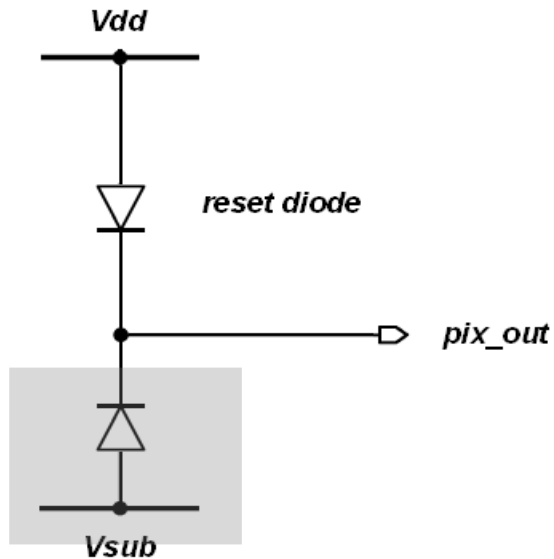
Reset schemes



Active reset

In active-reset pixels a PMOS *reset transistor* is used to reset the sensor. The gate is driven by a digital signal *PIX_RESET*.

When *PIX_RESET* = 0 a current discharges the pixel capacitance. *PIX_RESET*

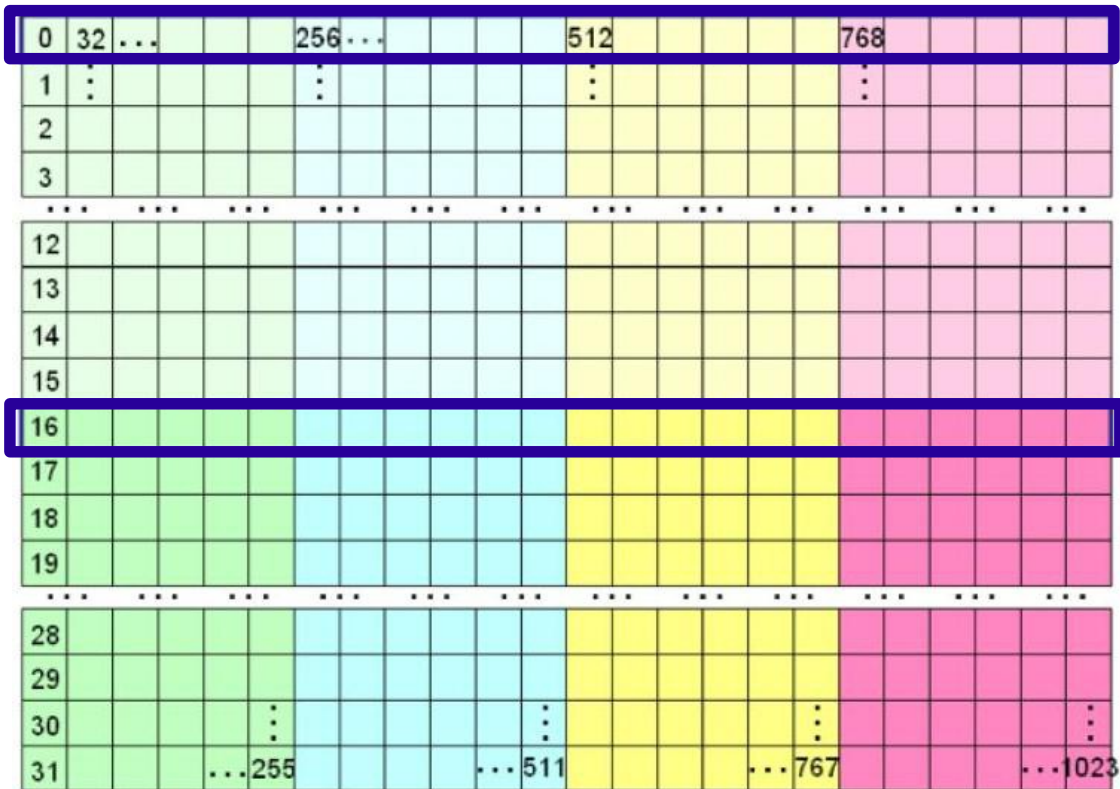


Continuous reset

Continuous-reset pixels discharge the sensor capacitance through a *diode* connected to a DC voltage.

Pulsed rows

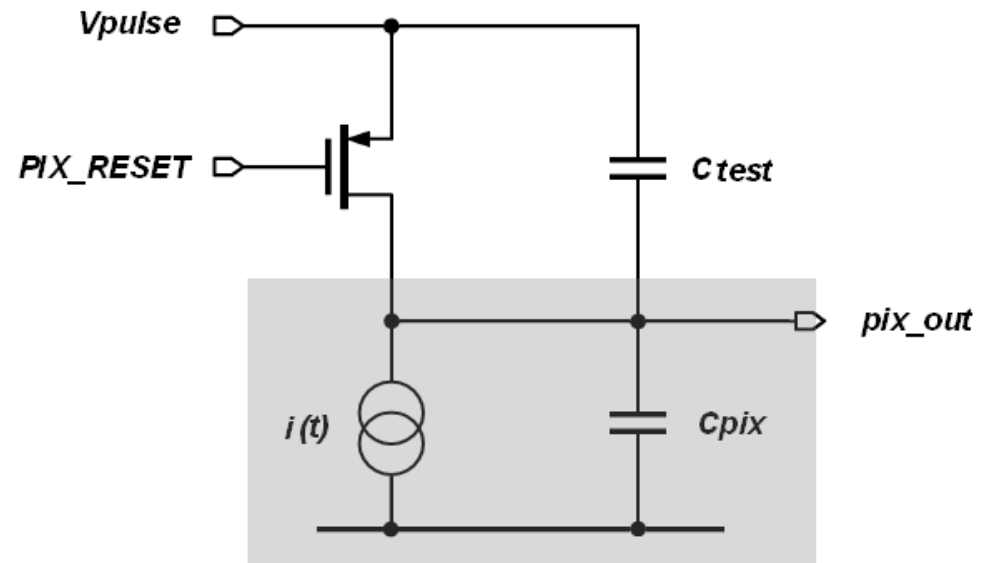
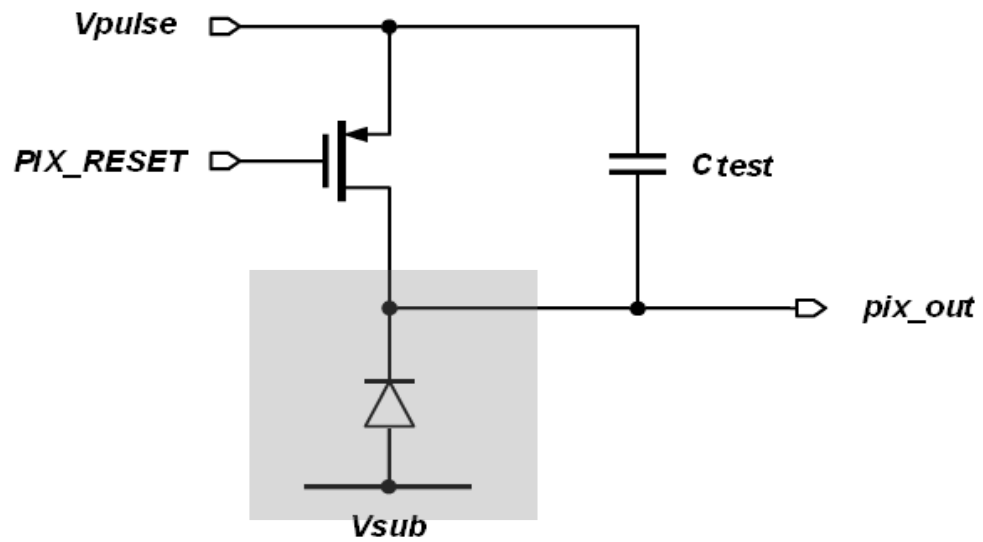
For testing purposes two rows (16 + 16 = 32 pixels) in the CORE part can be pulsed by using an external **test pulse** applied over a **test capacitance**



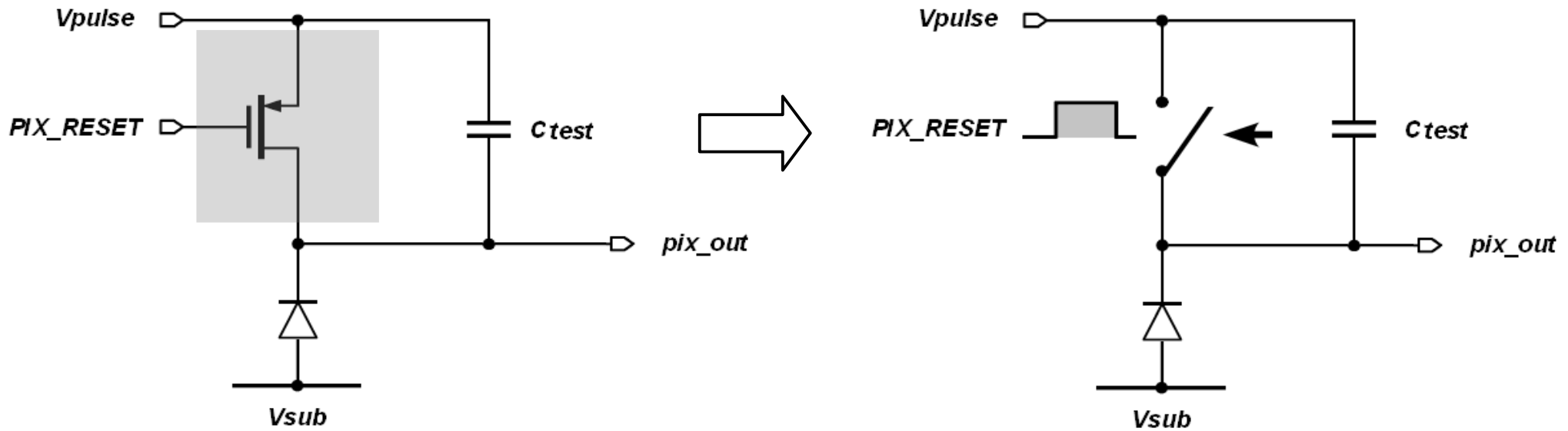
- 16 pixels with **active reset** (raw 0)

- 16 pixels with **continuous reset** (raw 16)

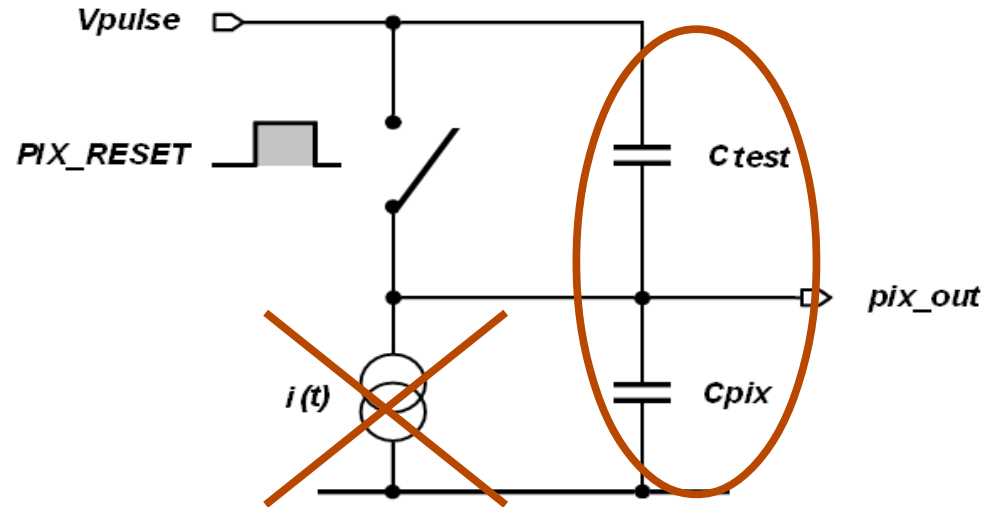
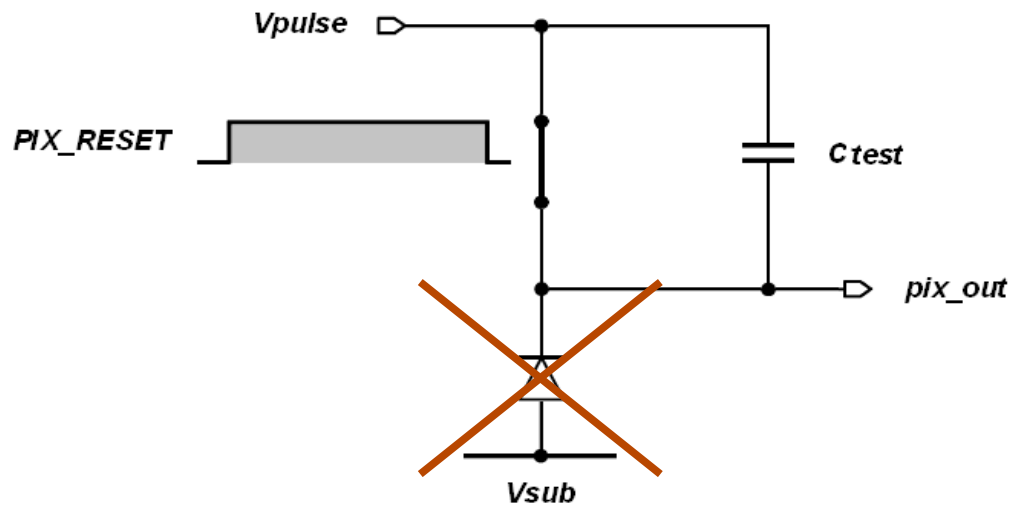
Sensor electrical model



Active reset + pulsed pixels (1)



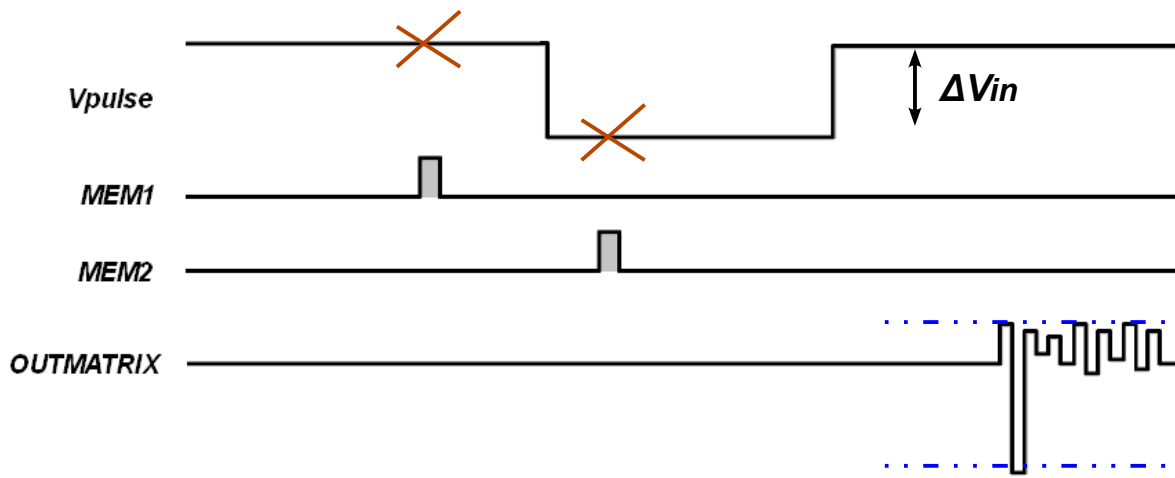
Active reset + pulsed pixels (2)



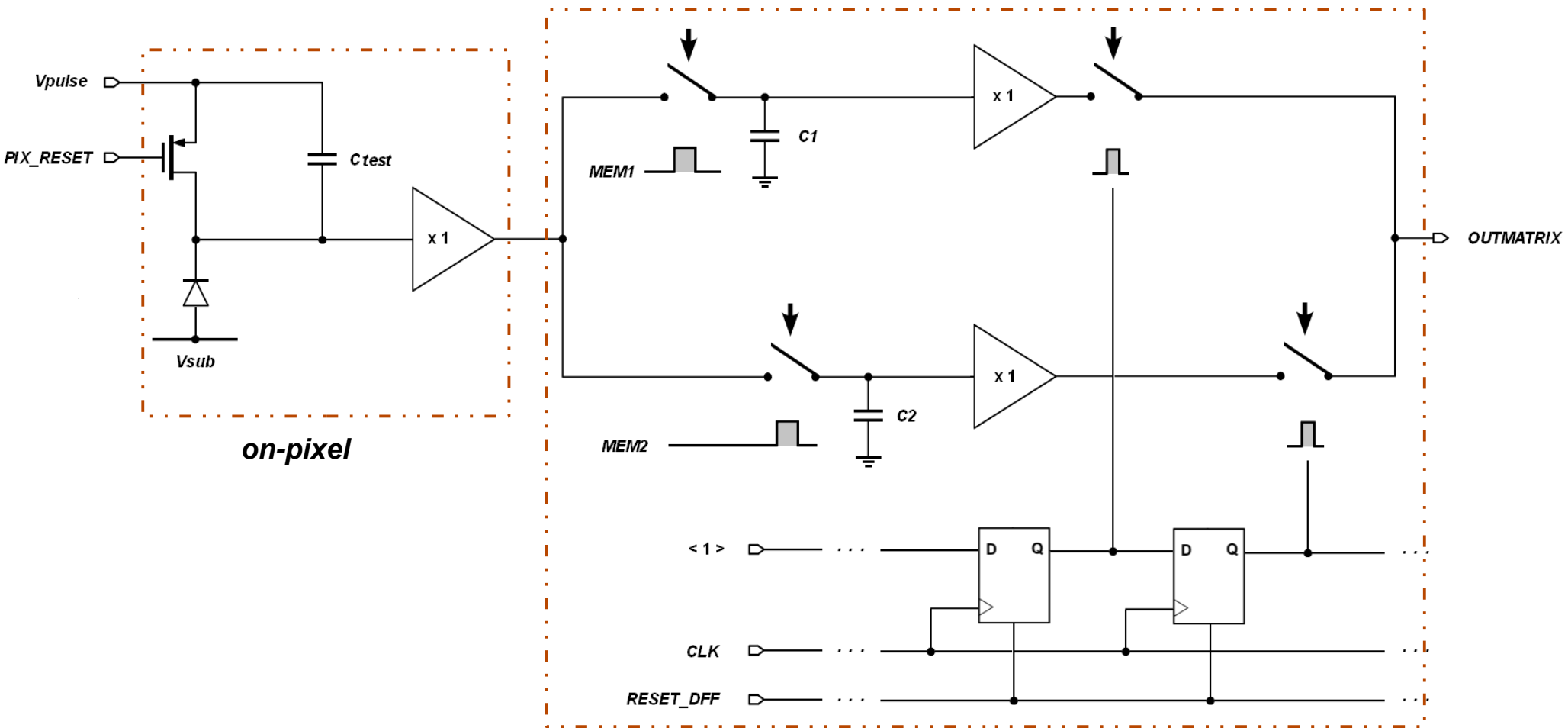
- **PIX_RESET** is kept high for the entire acquisition
 - PMOS switch ~short circuit
 - **$pix_out \approx V_{pulse}$**
- the sensor is **excluded** from the read-out !
 - useful configuration for **electronics-only characterizations**

- **PIX_RESET** is a short pulse (a few clock cycles)
 - the switch opens when **PIX_RESET** goes low
 - $i(t) = 0$ (you will not perform a test beam!)
 - test and sensor capacitances form a simple **capacitive divider**
- an estimation of the sensor capacitance C_{pix} can be obtained by applying a test pulse **V_{pulse}**

On-chip S/H read-out

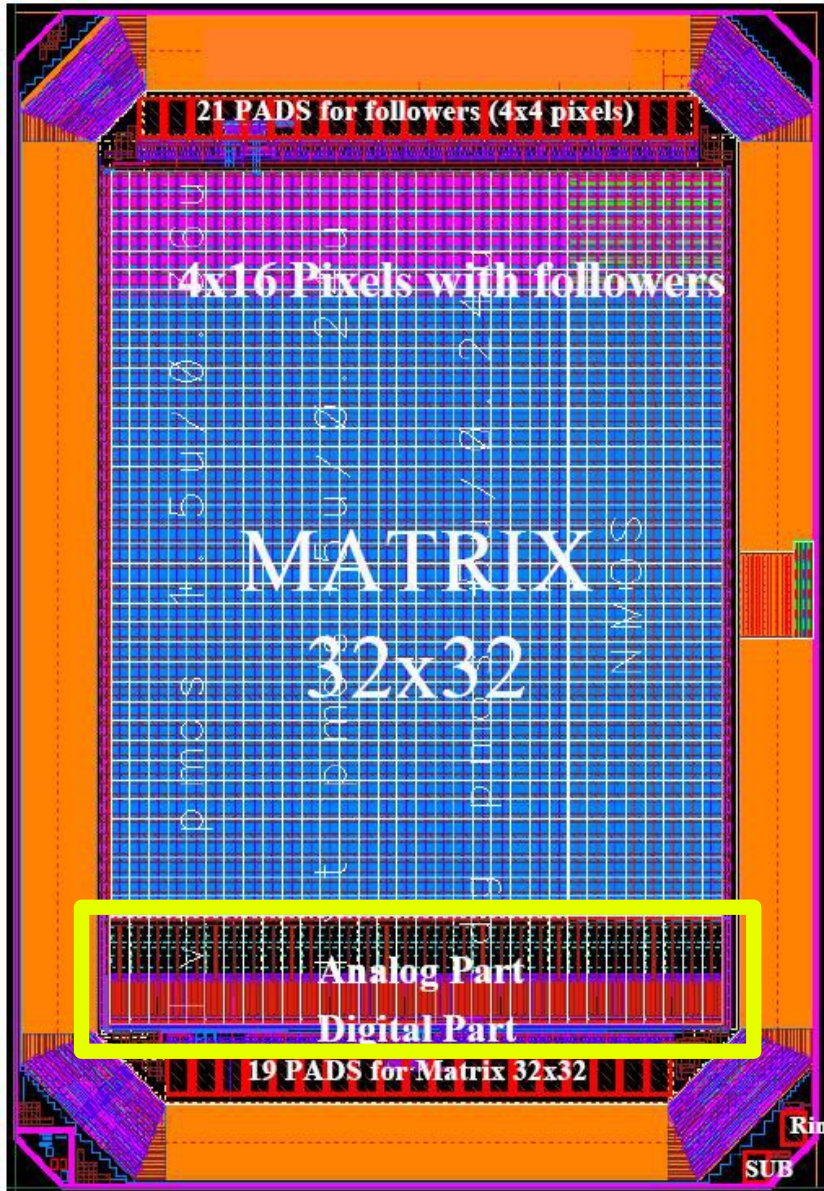


ΔV_{out}



on-pixel

in the chip periphery



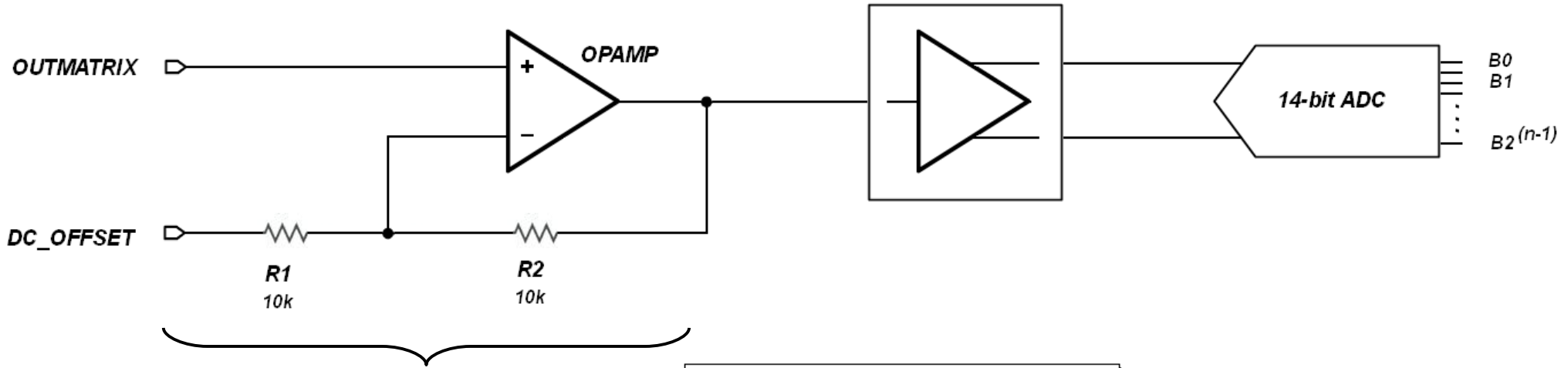
Analog and digital circuits are built in the *chip periphery* and *integrated* on the same sensor silicone die !

analog part

digital part

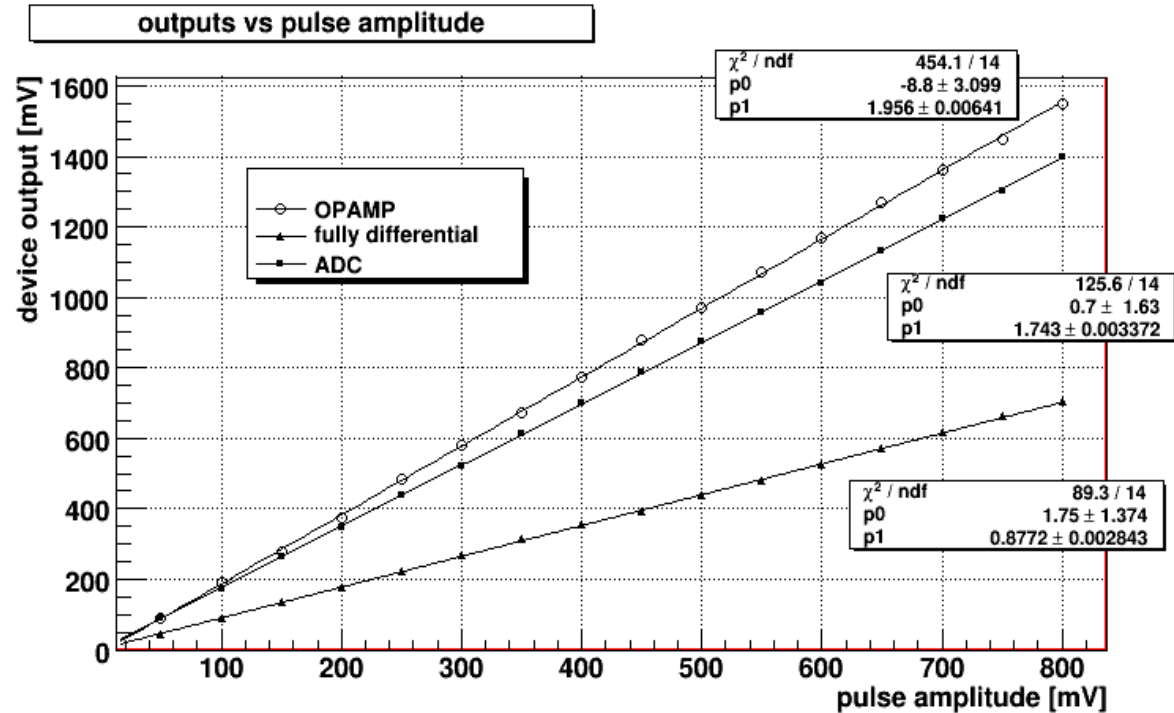
Off-chip read-out

single ended → fully differential



non inverting amplifier

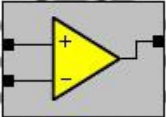
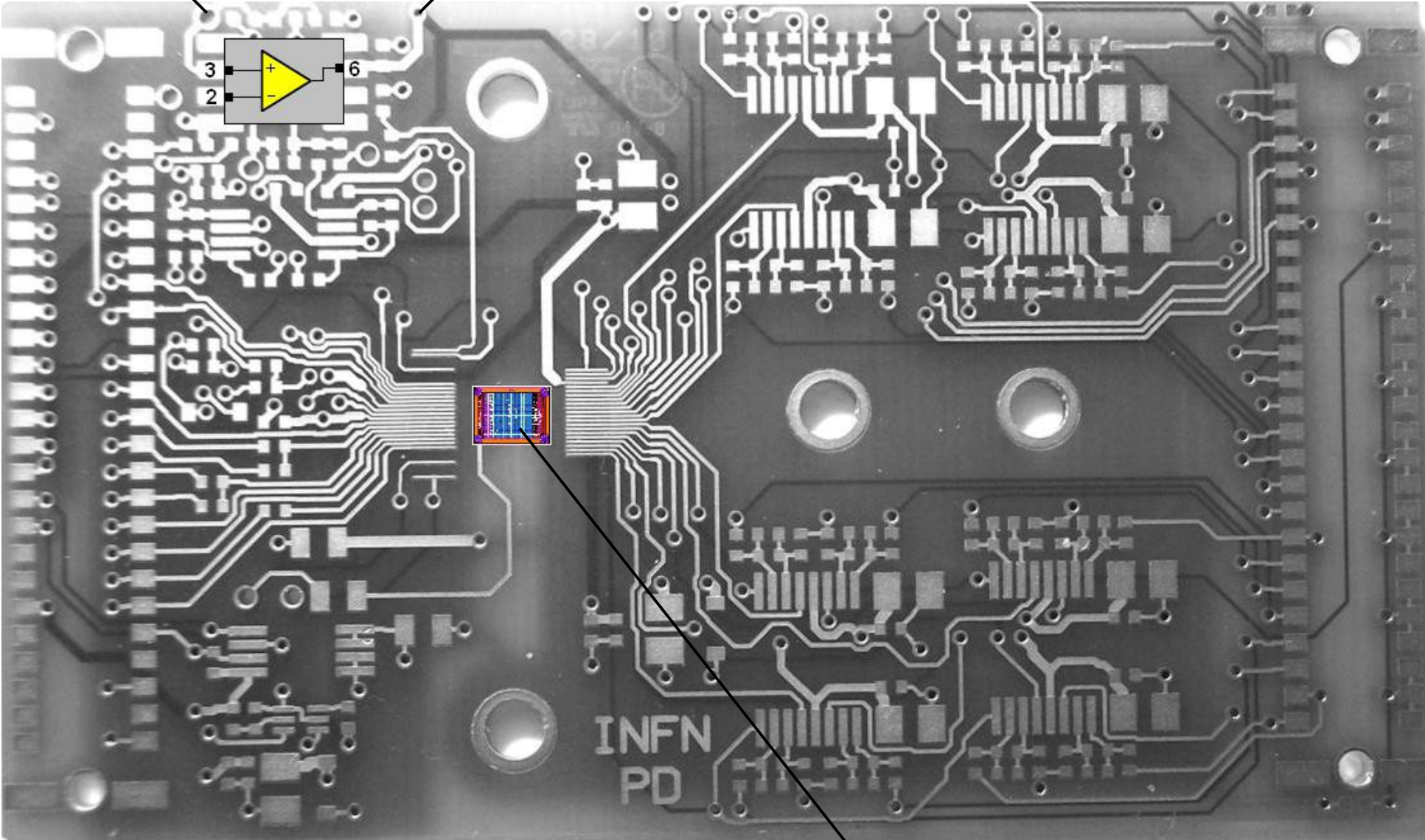
$$(A_v = 1 + R2/R1)$$



Chip mezzanine (1)

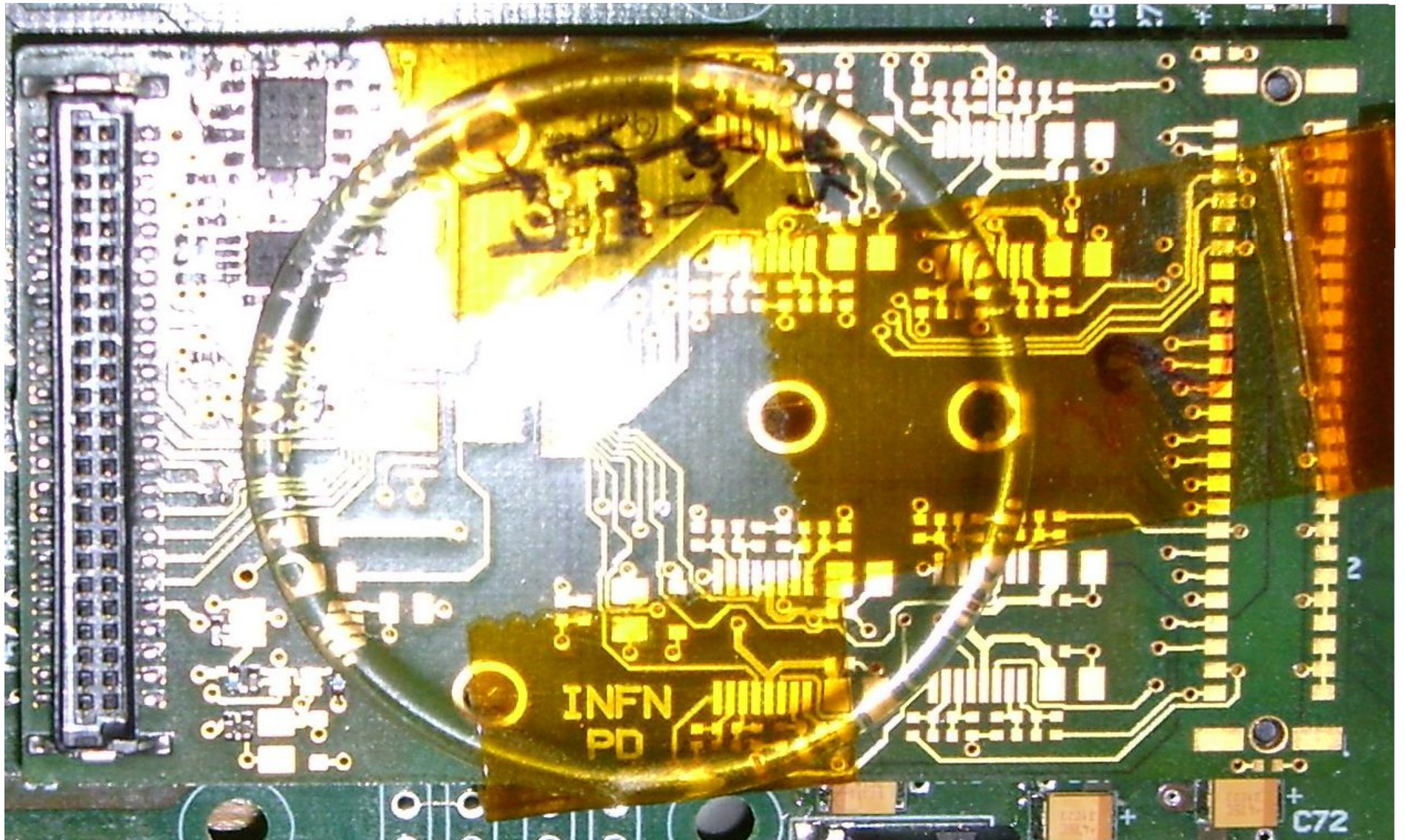
OUTMATRIX

OPAMP output



LePix chip

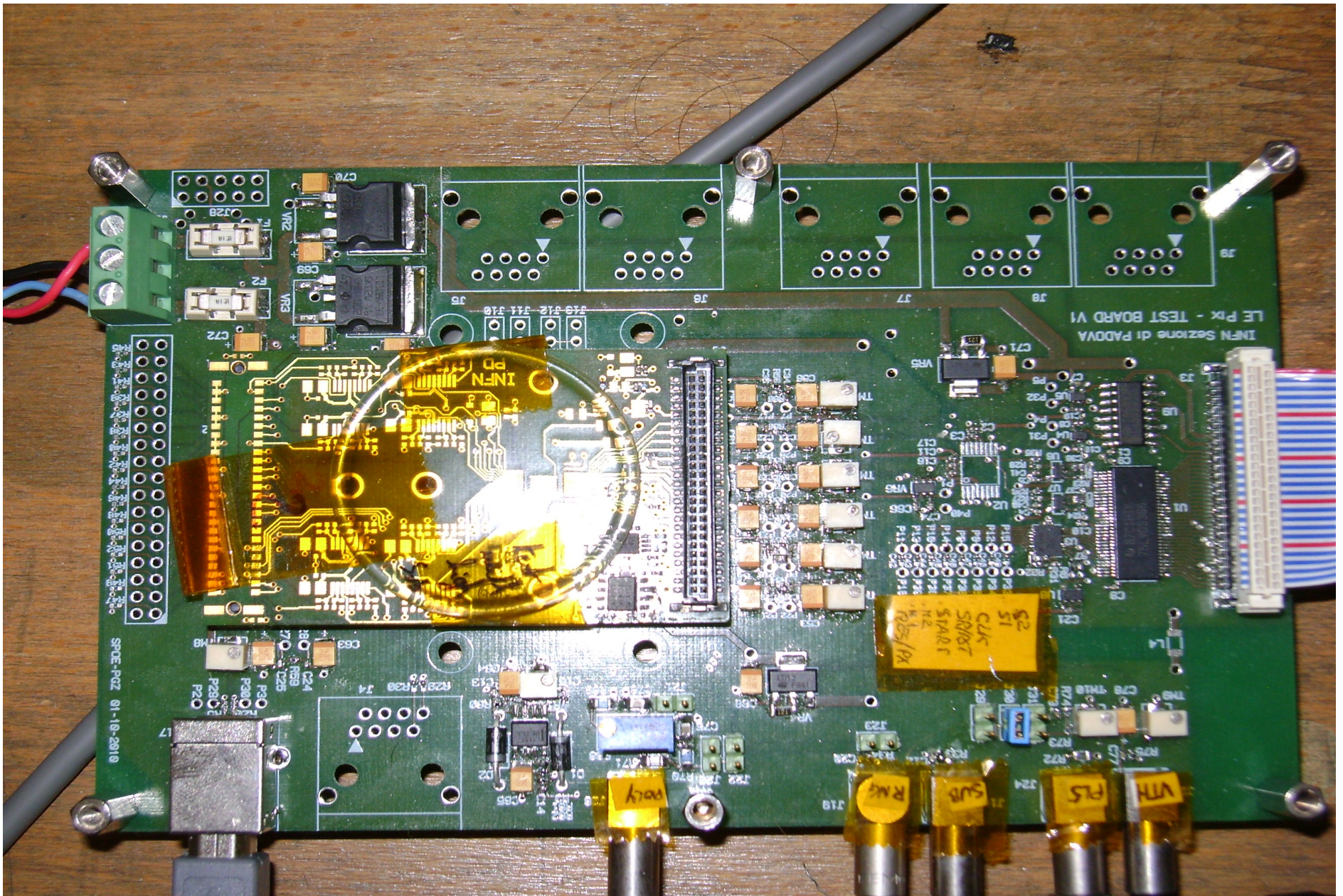
Chip mezzanine (2)



Test PCB (1)

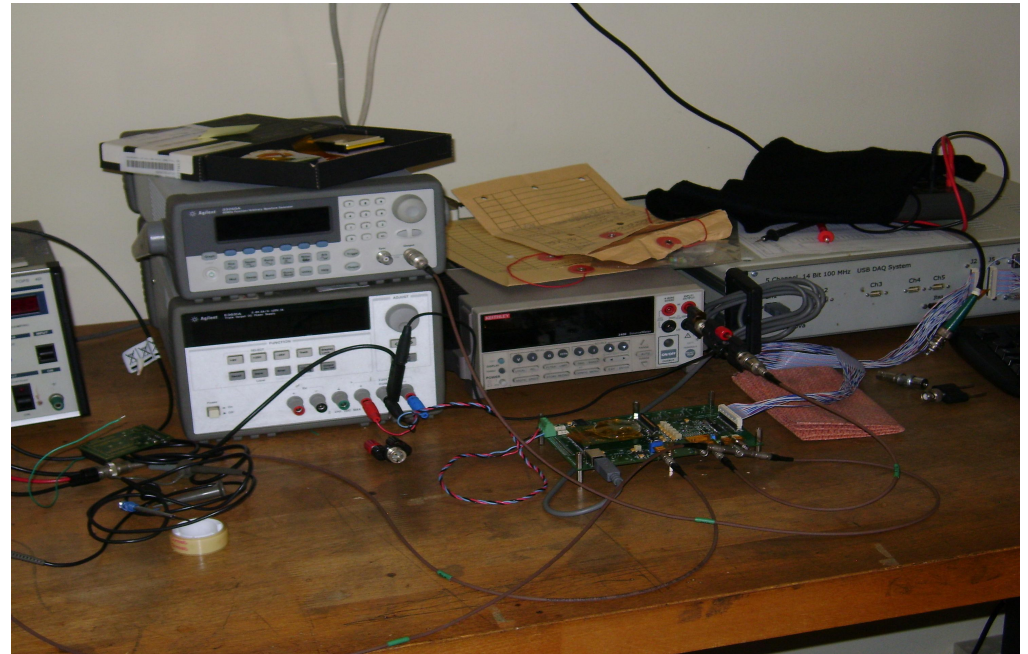


Test PCB (2)



Experimental setup

- plug-and-play mezzanine
- test PCB
- power supplies
 - test PCB biasing (± 5 V)
 - sensor depletion voltage (max. -30 V)
 - parasitic transistors
- pulse generator
- digital oscilloscope
- DAQ (14-bit ADC with USB interface)
- computer with acquisition interface



DAQ interface (1)

SOI Imager Test Beam - (C) Piero Giubilato 2010

Commands

- Start
- Pedestal
- Comm RESET
- Save
- Quit

Acquisition

Acquisition mode: Soft single shot
Data manipulation: Raw data
Spill length (s)/Spill count: 1 / 1
Detector configuration: LePix Matrix 1&2 1Ch
Bursts: 10 | Frames: 16
Data source: ADCs data
Frequency: 100 KHz
Averages: 1 | Delay: 1
Ch 1 Ch 2 Ch 3 Ch 4

LePix Specific

START begin: 1 | START end: 250
RESET begin: 4 | RESET end: 8
VPULSE begin: 30 | VPULSE end: 34
MEM1 begin: 20 | Rdout cnt: 2048
MEM2 begin: 40
PX RST begin: 12 | PX RST end: 16

Fileserver

Raw file: Off | Null
file: Off | Null
Mult THR: 1
Mult MAX: 1

Pedestals

Auto pedestal
Frames count: 32

Status

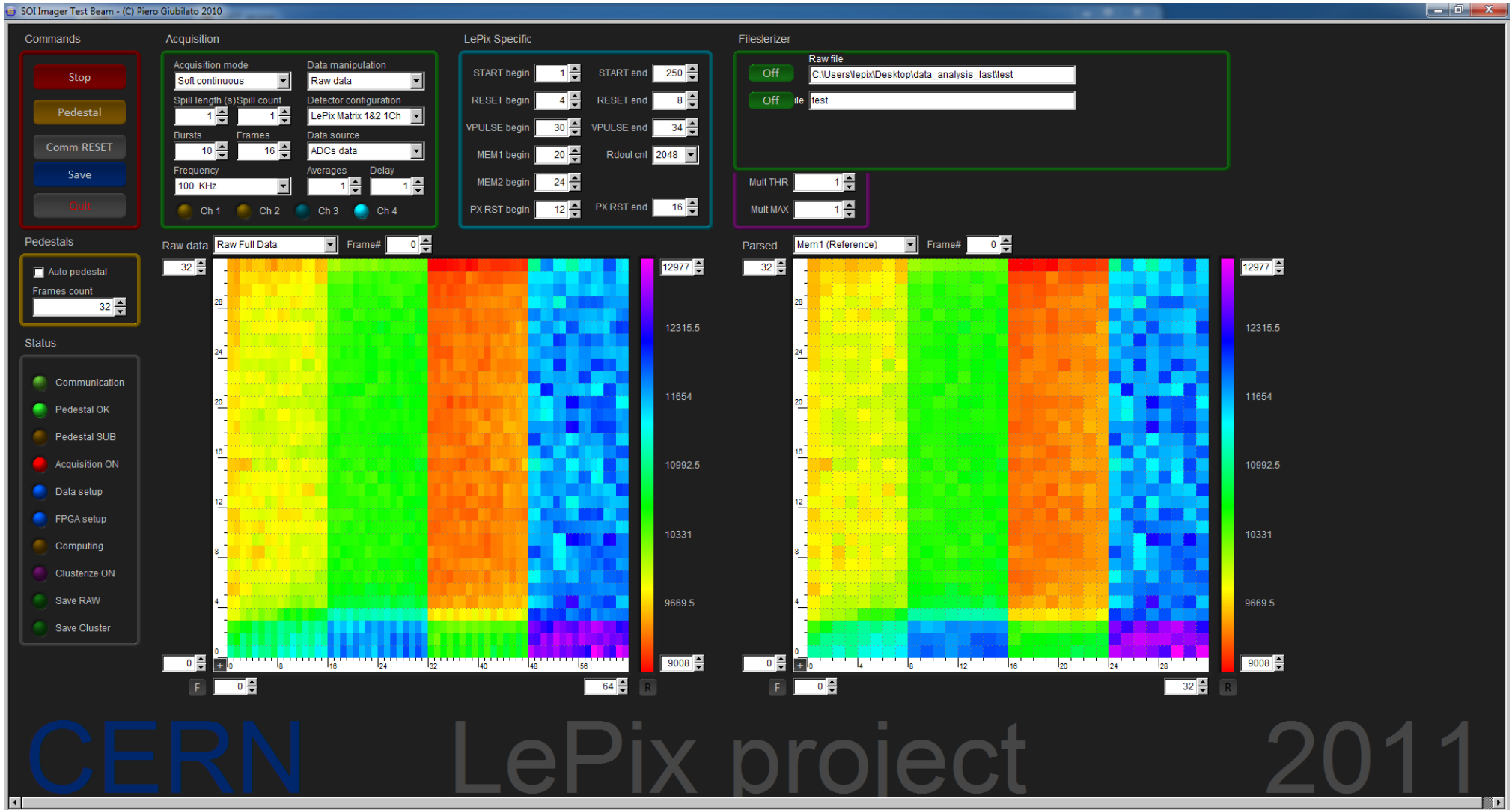
- Communication
- Pedestal OK
- Pedestal SUB
- Acquisition ON
- Data setup
- FPGA setup
- Computing
- Clusterize ON
- Save RAW
- Save Cluster

Raw data Raw Full Data | Frame# 0

Parsed Mem1 (Reference) | Frame# 0

CERN LePix project 2011

DAQ interface (2)



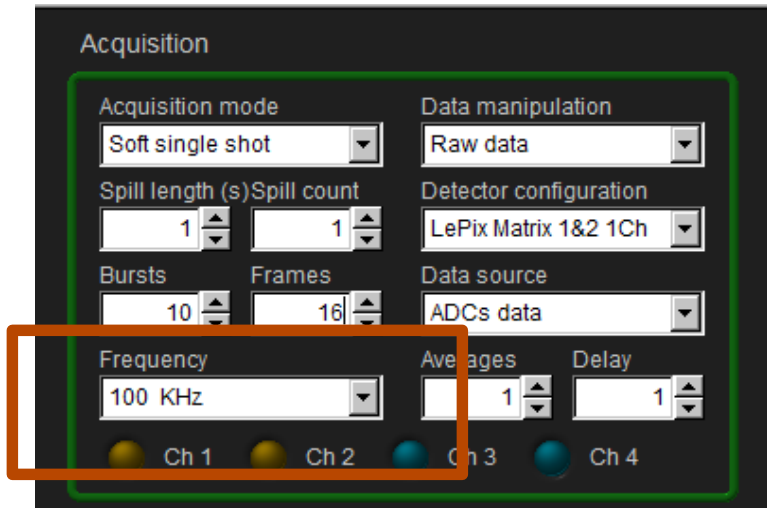
CERN

LePix project

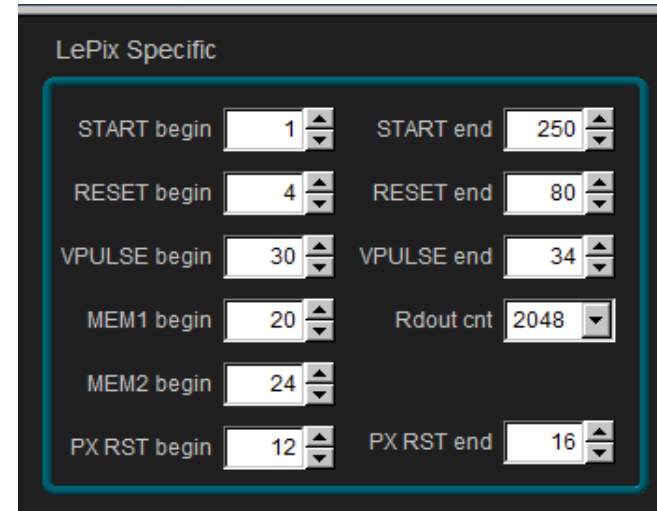
2011

Control signals – DAQ interface

The *timing* for digital control signals is set from DAQ interface



CLK

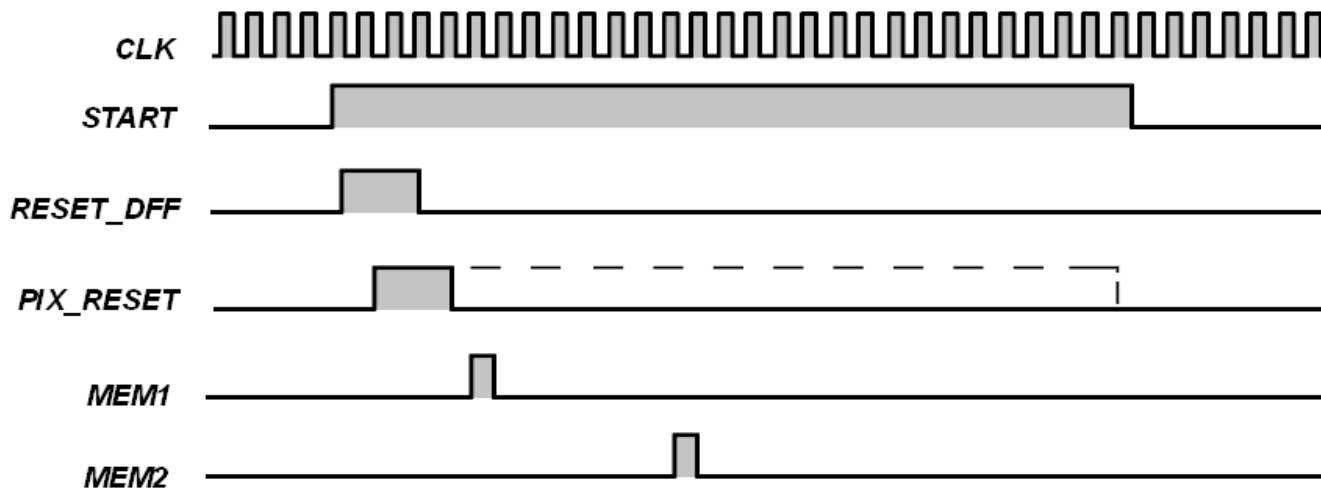


START
RESET_DFF

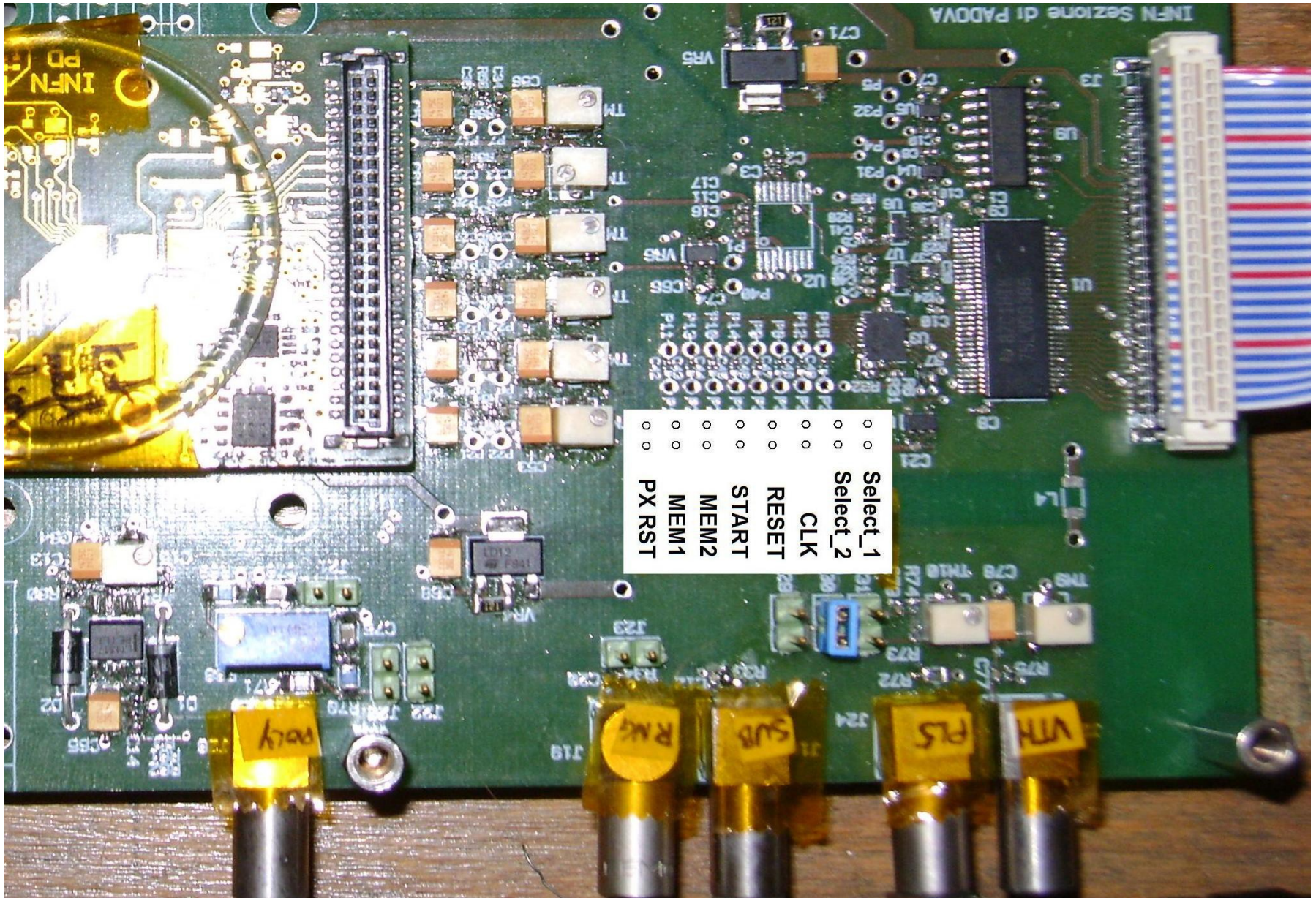
MEM1
MEM2

PIX_RESET

(start/stop are defined in term of $n = n$ clock cycles)



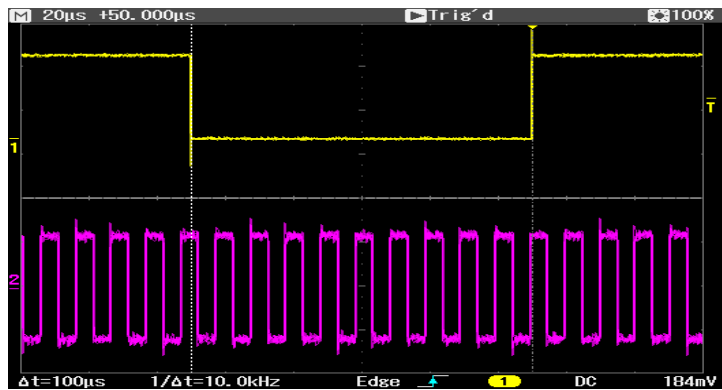
Control signals on the test PCB



Control signals at the oscilloscope

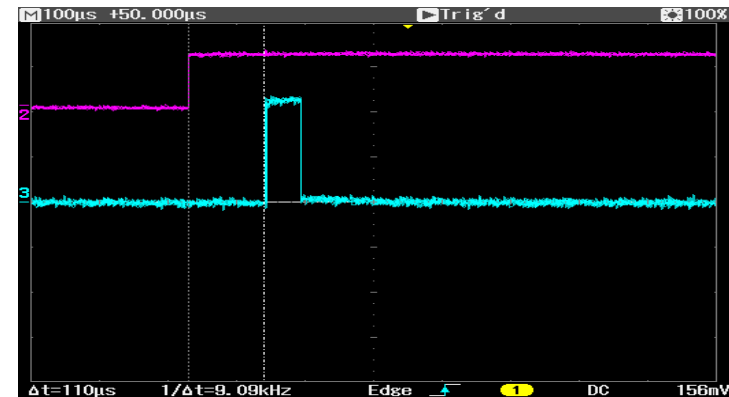
Getting started

Set a right timing for the control signal (check it out using the oscilloscope!)



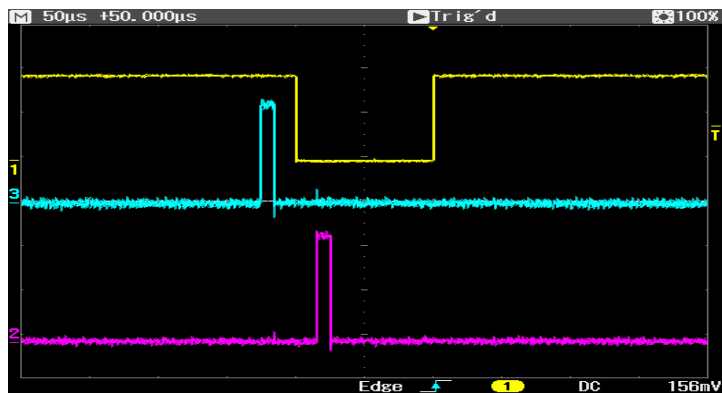
Vpulse

CLK



START

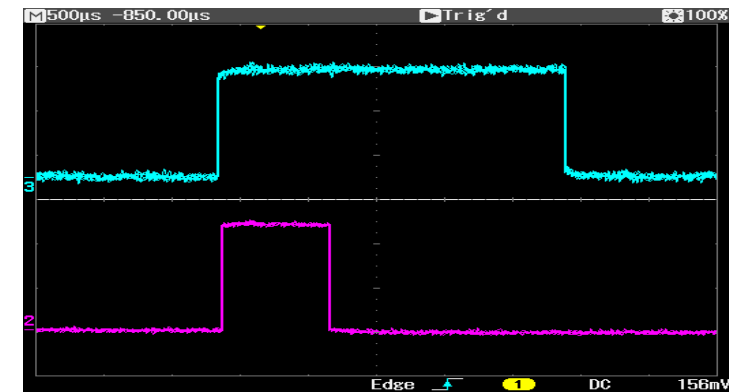
PIX_RESET



Vpulse

MEM1

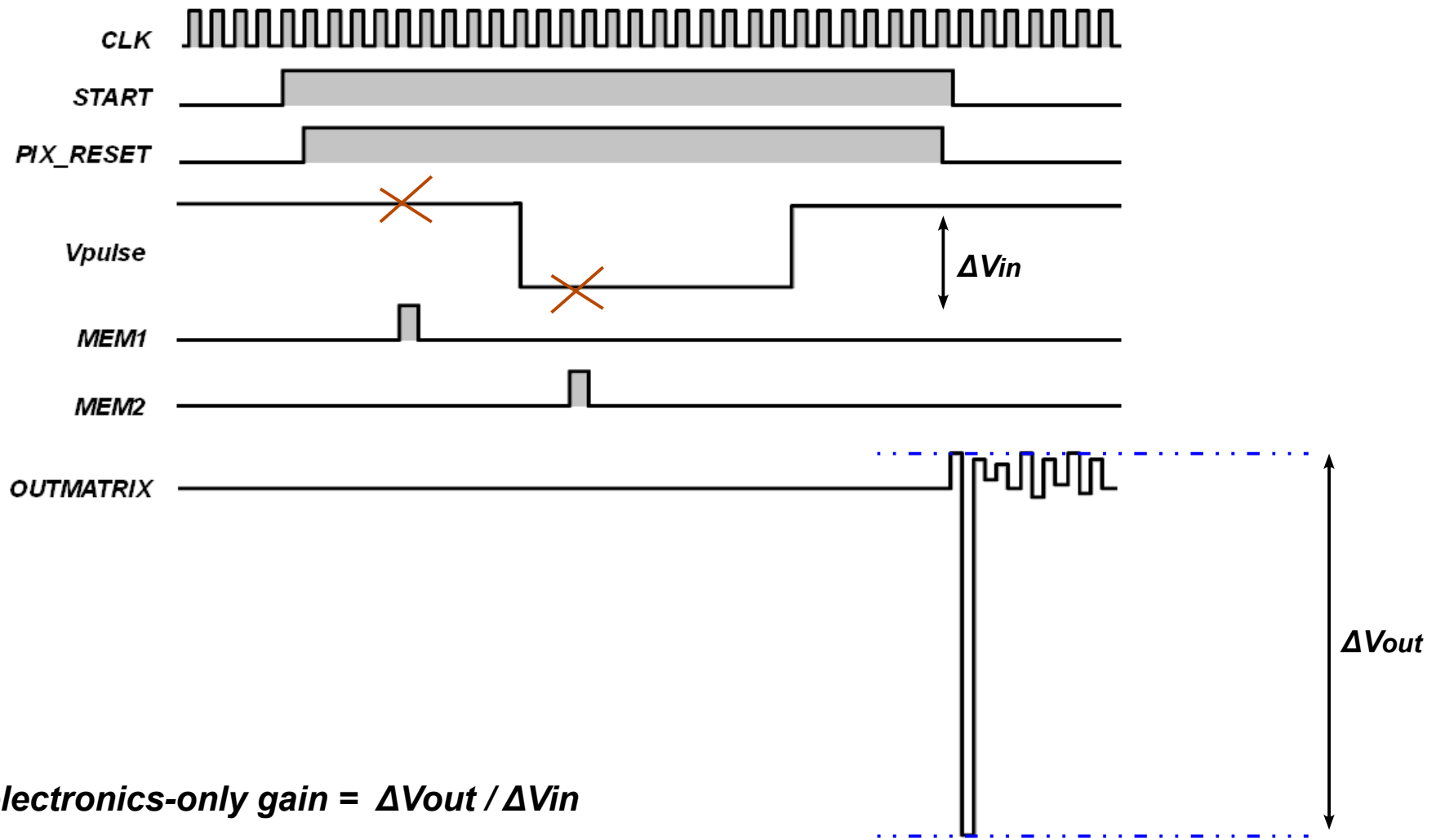
MEM2



START

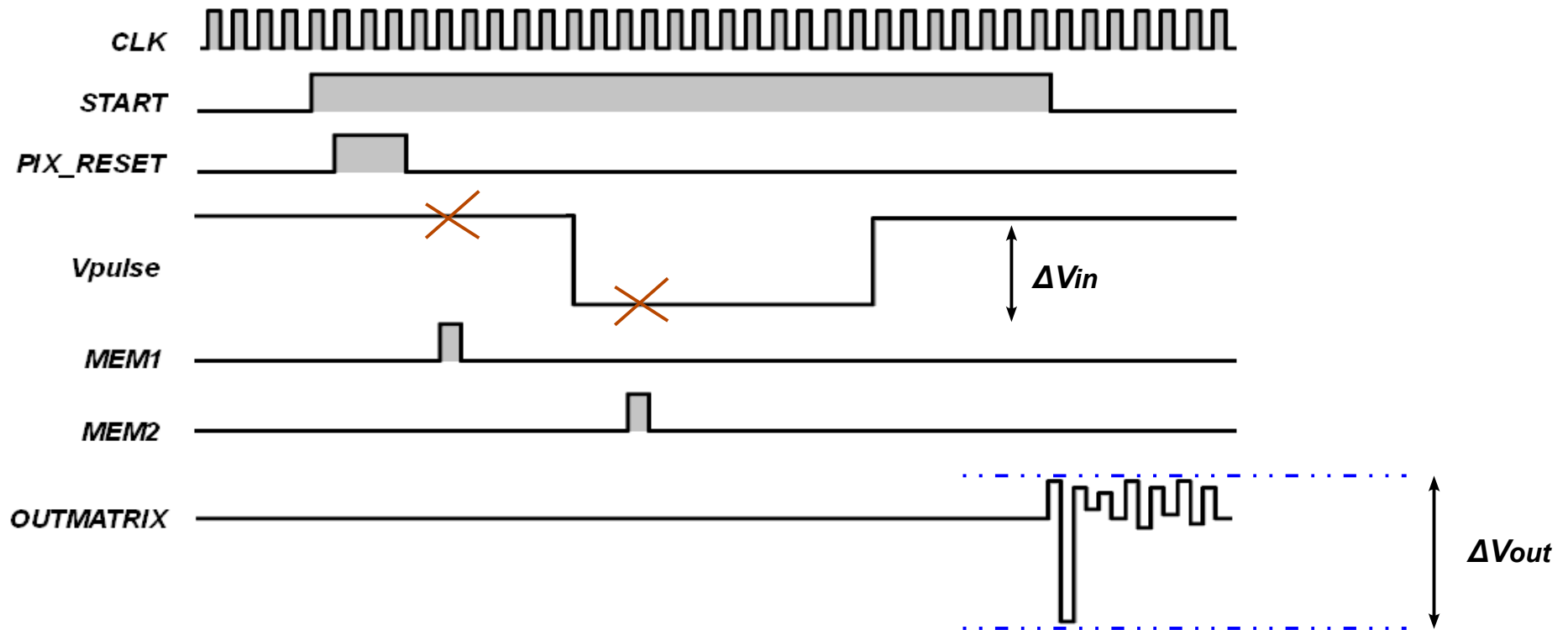
DFF_RESET

Test pulse measurements (1)



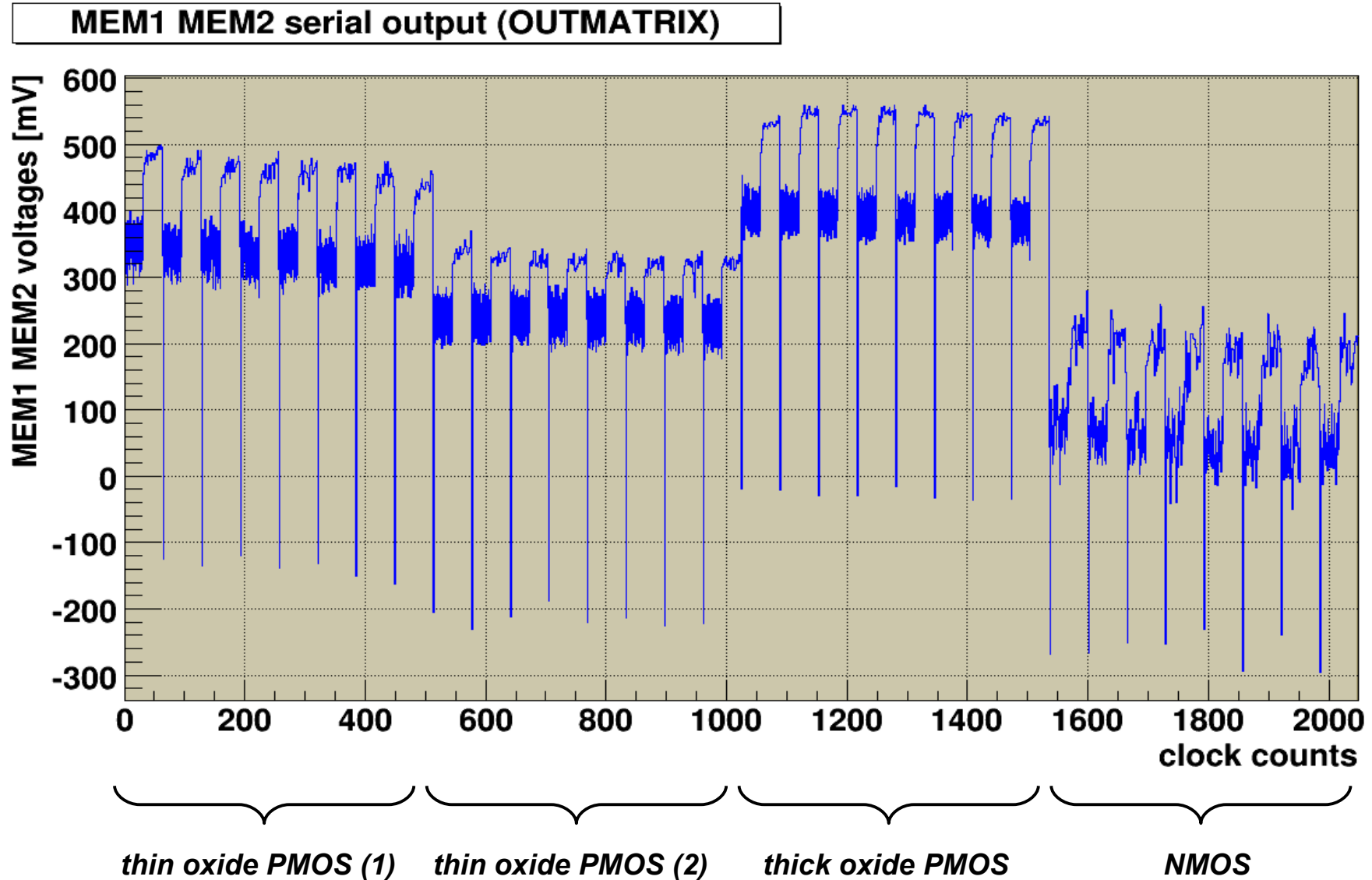
electronics-only gain = $\Delta V_{out} / \Delta V_{in}$

Test pulse measurements (2)

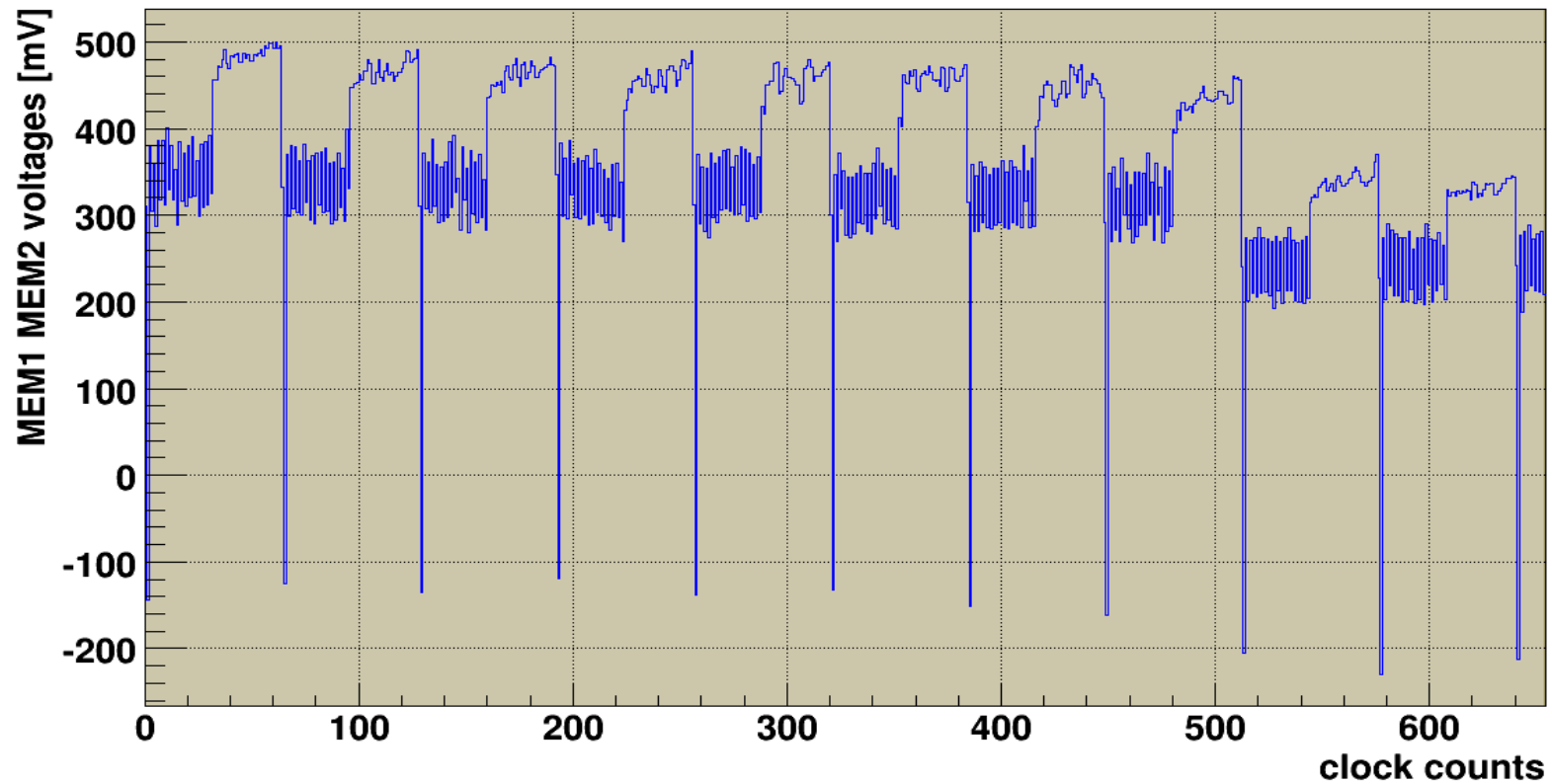
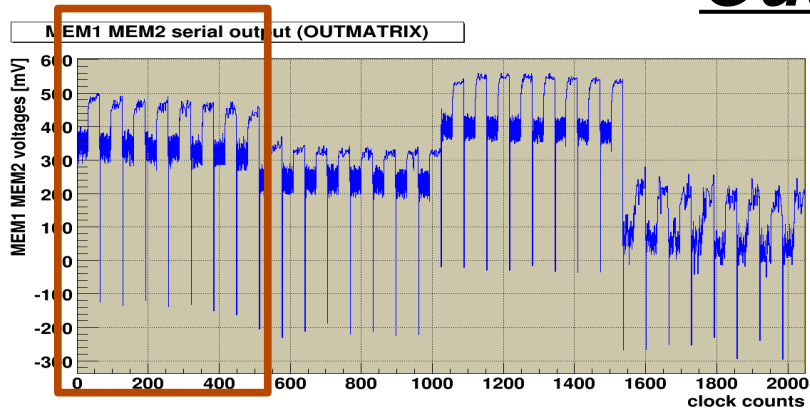


total gain (sensor + electronics) = $\Delta V_{out} / \Delta V_{in}$

Output waveform (OUTMATRIX) (1)

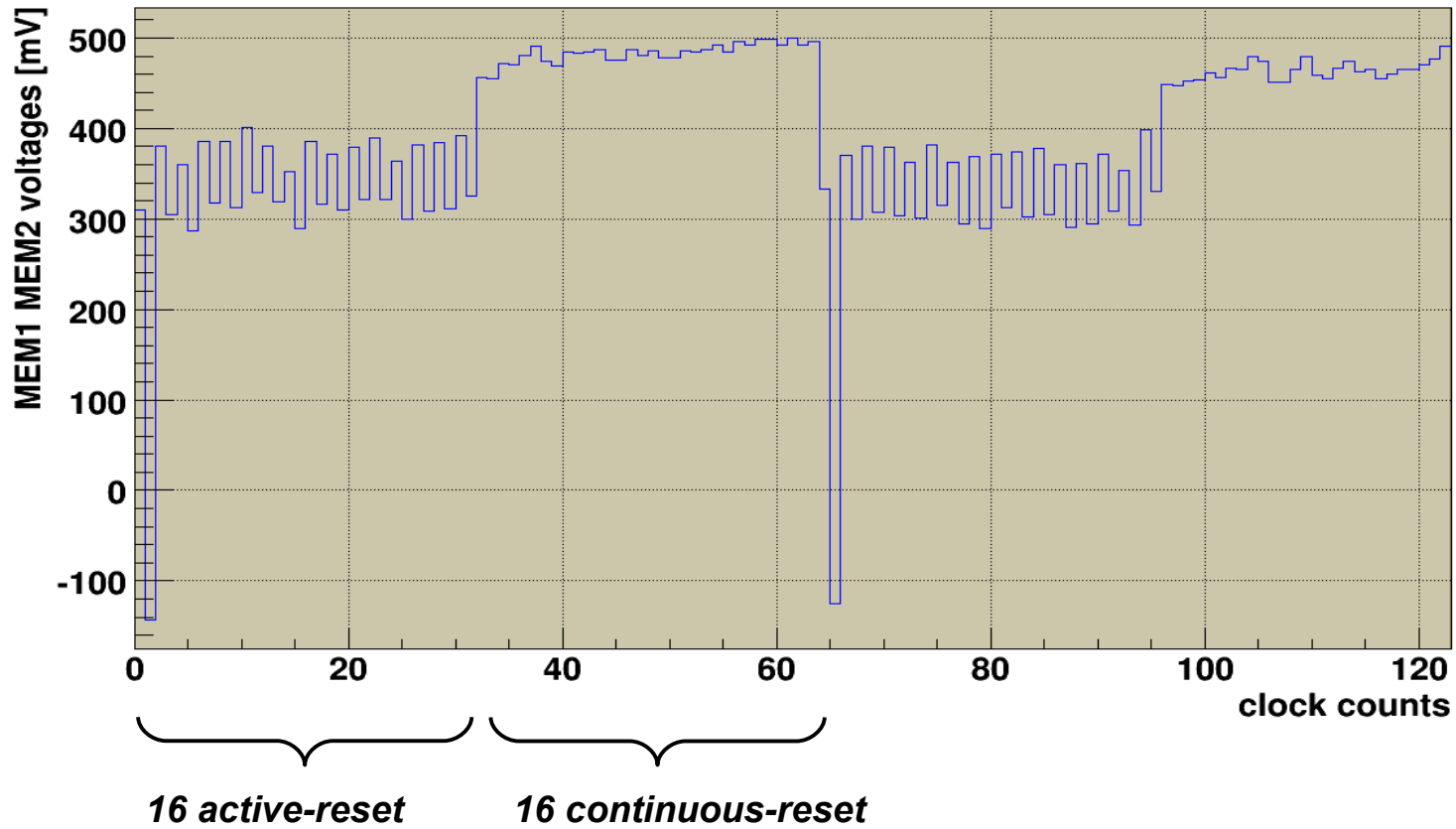
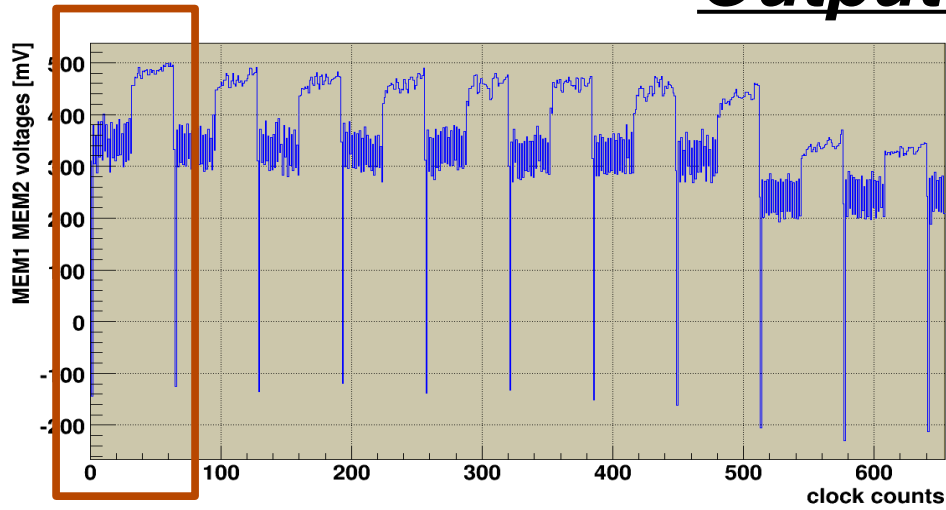


Output waveform (OUTMATRIX) (2)

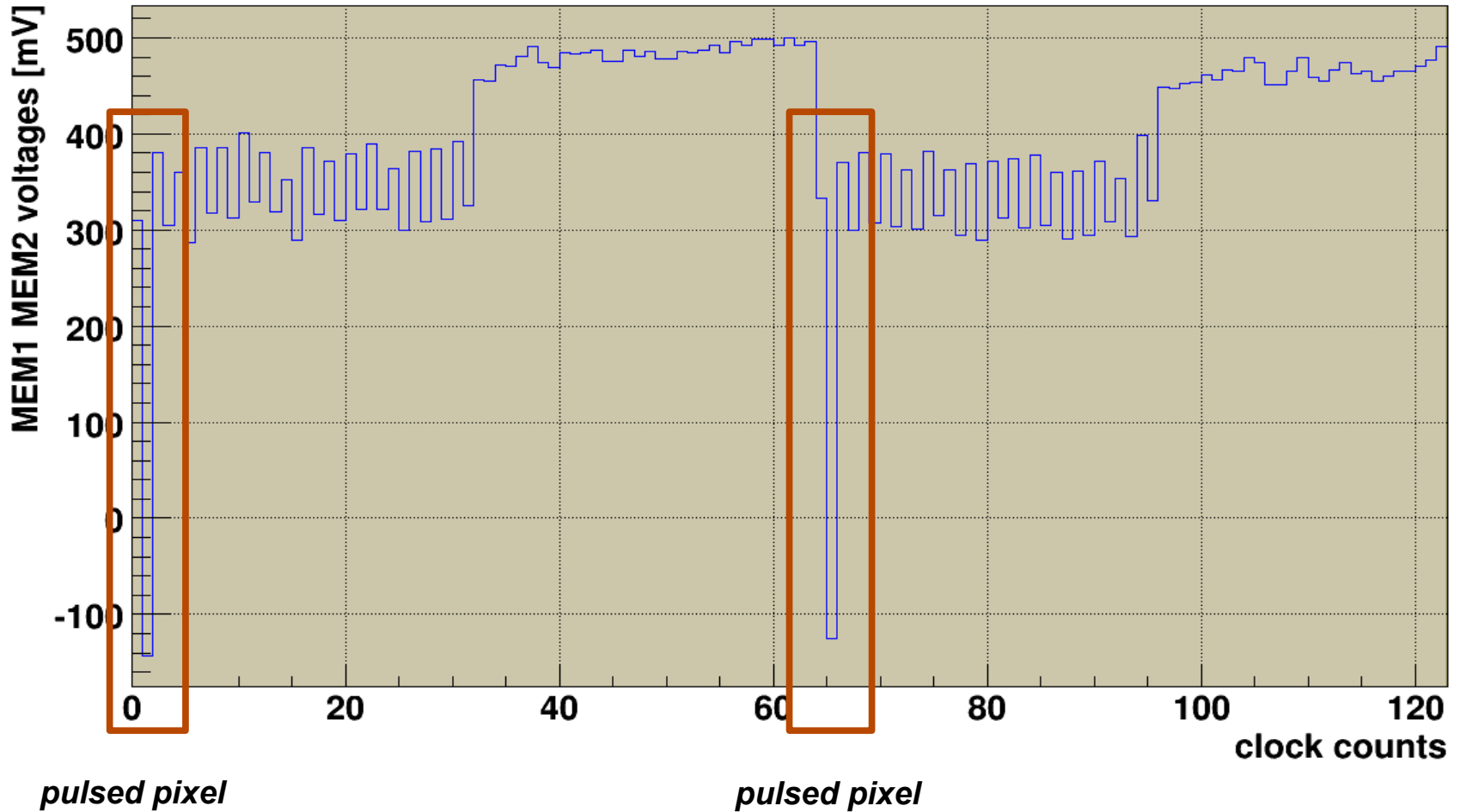


8 columns

Output waveform (OUTMATRIX) (3)



Output waveform (OUTMATRIX) (4)



Lab measurements (1)

Electronics gain measurements

Measure ΔV_{out} at the oscilloscope for the first pulsed pixel by applying test pulses with different amplitudes ΔV_{in}

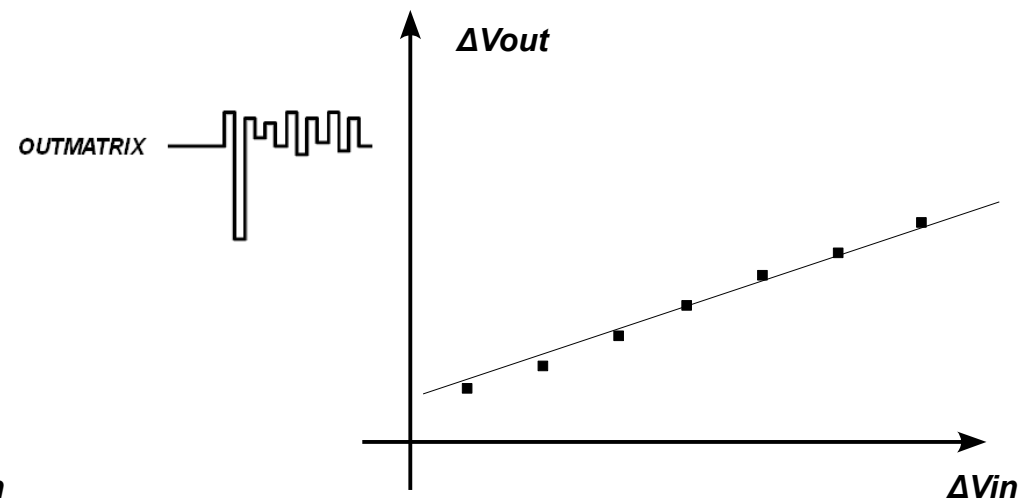
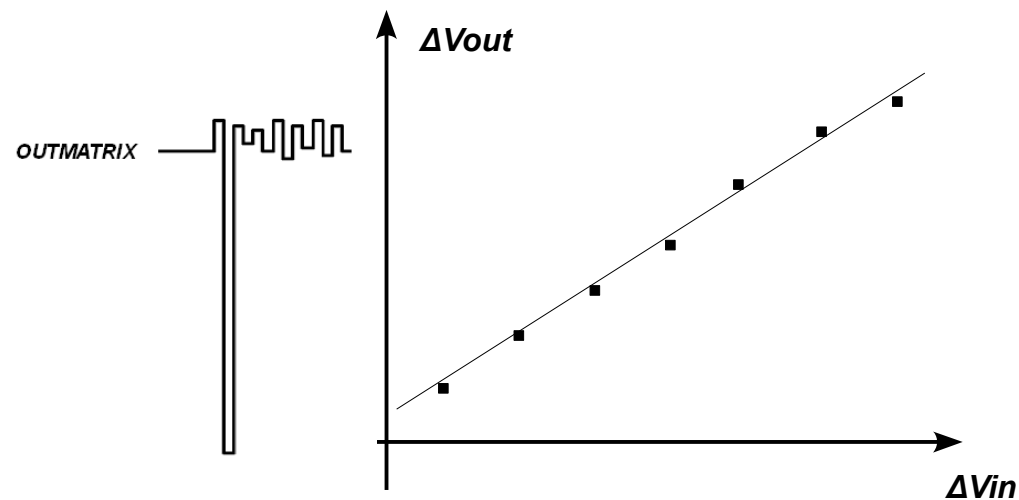
- excluding the sensor from read-out (**PIX_RESET** always on) → electronics-only gain
- including the sensor capacitance → sensor + electronics gain

electronics-only (PIX_RESET always ON)

ΔV_{in}	ΔV_{out}
100 mV	...
200 mV	...
...	...

sensor + electronics

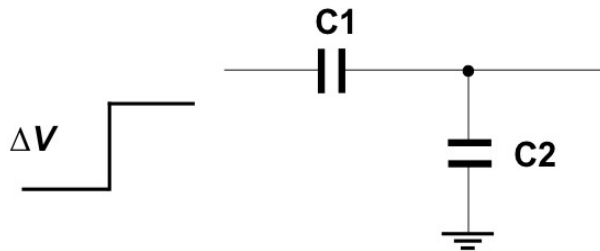
ΔV_{in}	ΔV_{out}
100 mV	...
200 mV	...
...	...



read-out voltage gain = $\Delta V_{out} / \Delta v_{in}$ → liner fit slope

Lab measurements (2)

Refresh



$$V' = V_0 + \frac{C_1}{C_1 + C_2} \Delta V$$

capacitive divider formula

Sensor capacitance estimation

An estimation of the pixel depletion capacitance can be obtained from electronics gain measurements:

$$\text{total gain} = (\text{electronics-only gain}) \times (\text{capacitive divider ratio})$$

from linear fits

$$\left(\frac{C_{test}}{C_{pix} + C_{test}} \right)$$

$$C_{test} = 1 \text{ fF (10\%)} \\ \text{(from specs)}$$

Make a comparison with capacitance values obtained for silicon strips...